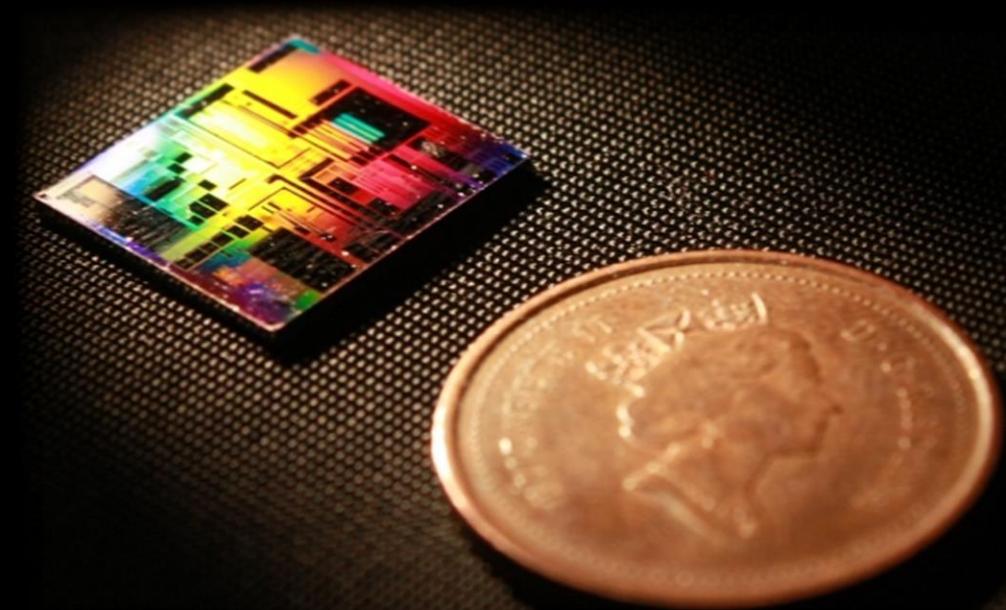


# CONTRA-DIRECTIONAL COUPLERS

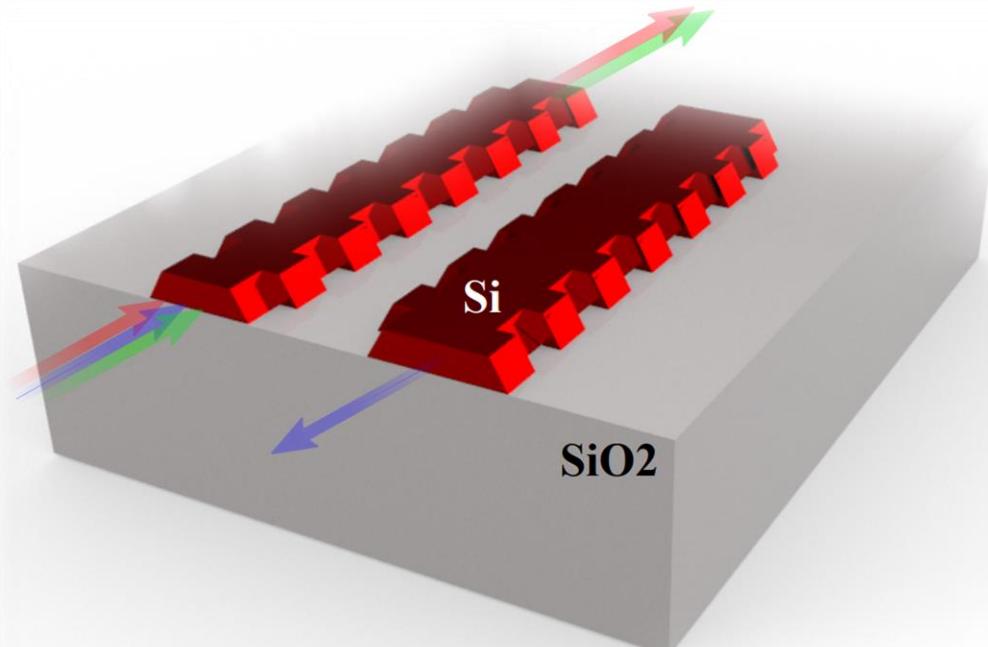
Mustafa Hammood

2020-11-26



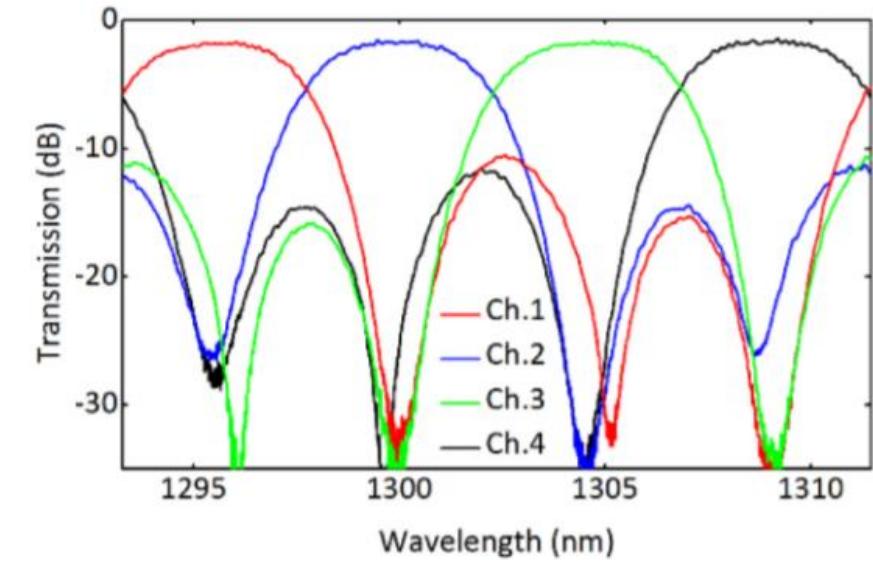
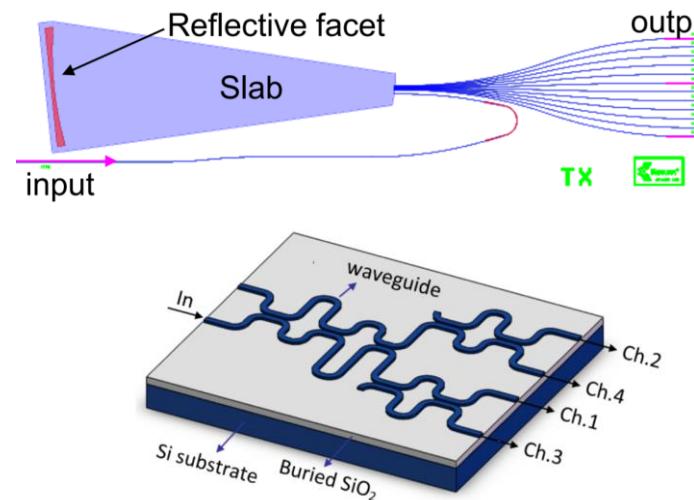
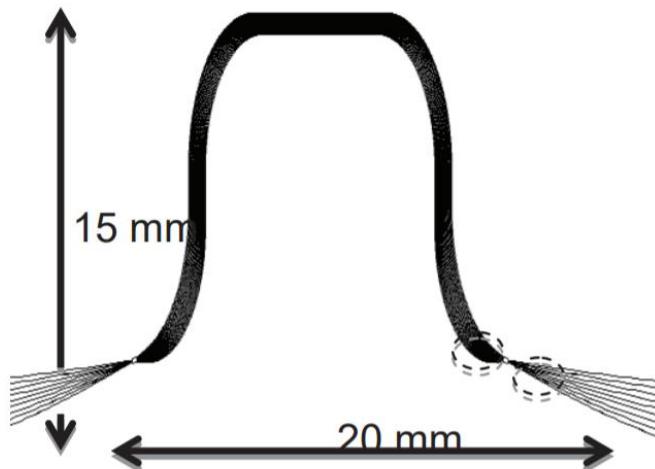
# OUTLINE [1.5 HOURS]

- **Introduction** [20 mins]
  - WDM Filters on Integrated Photonics
  - Theory and photonic band diagrams
- **Practical Design Challenges**
  - Lithography Modelling
  - Fabrication imperfections and variations
- **Designs and applications** [20 mins]
  - Cascaded filters
  - Multi-mode gratings
  - FSR-free rings and modulators
  - Sub-wavelength grating
- **Modeling and design activity** [25 mins]
  - Coupled-mode theory + Transfer Matrix method
  - Design your own WDM system



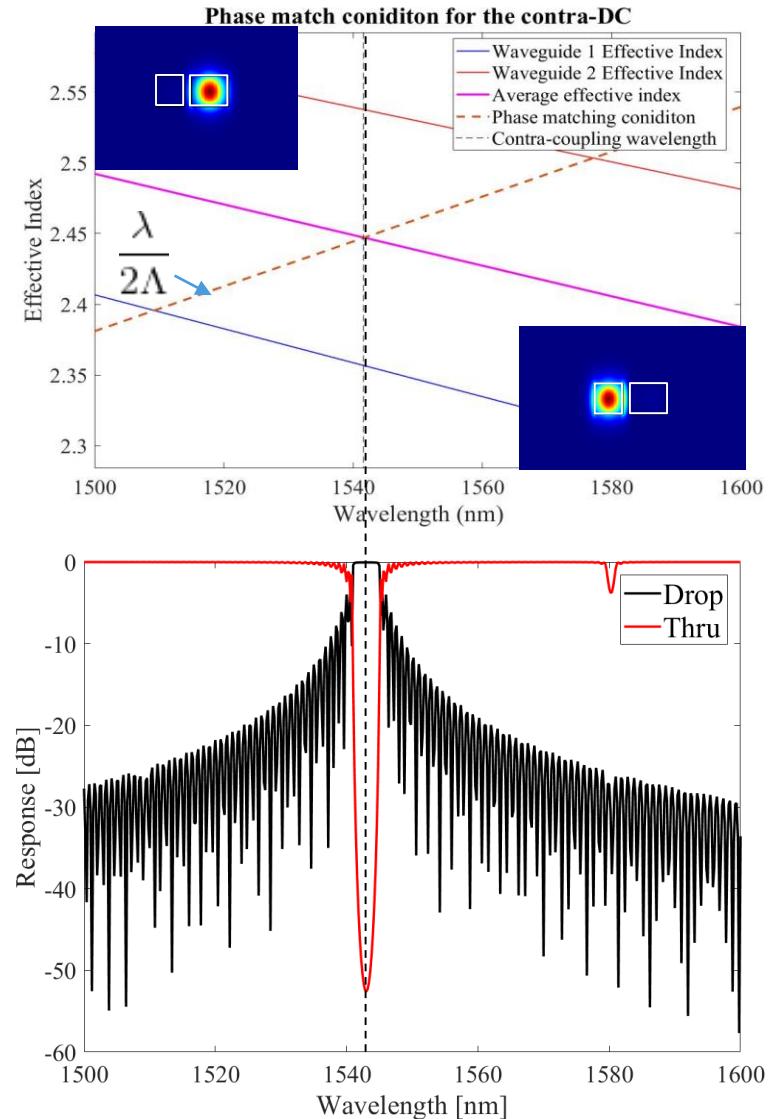
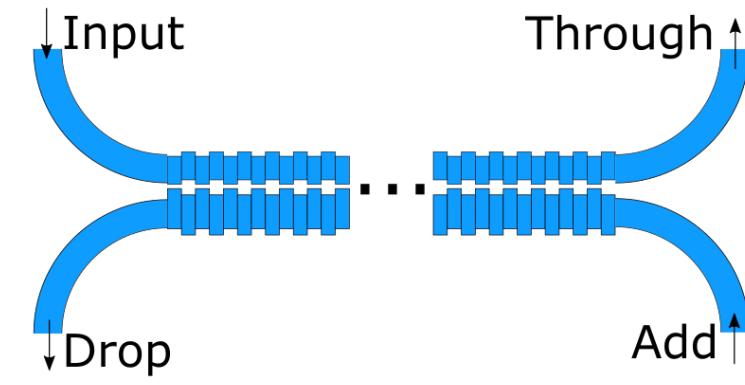
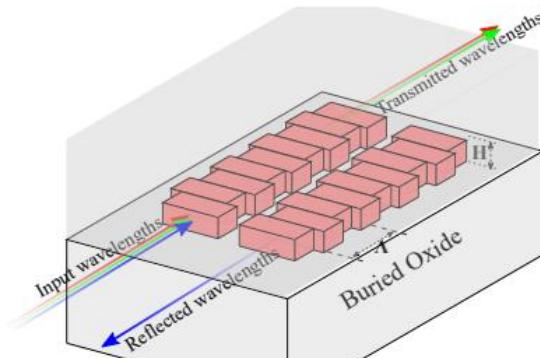
# WDM ON SILICON

- For Coarse Wavelength Division Multiplexing (CWDM): We need filters with large bandwidth, tolerant to laser's wavelength drift, suitable for short-reach data communication
- Fabrication variations are one of the major limitations on SOI-based photonics, realizing such systems on the SOI platform is important
- Approaches on SOI include: Echelle gratings, Arrayed Waveguide Gratings (AWGs), Echelle gratings, Mach-Zehnder lattice filters, and contra-directional couplers (contra-DCs).



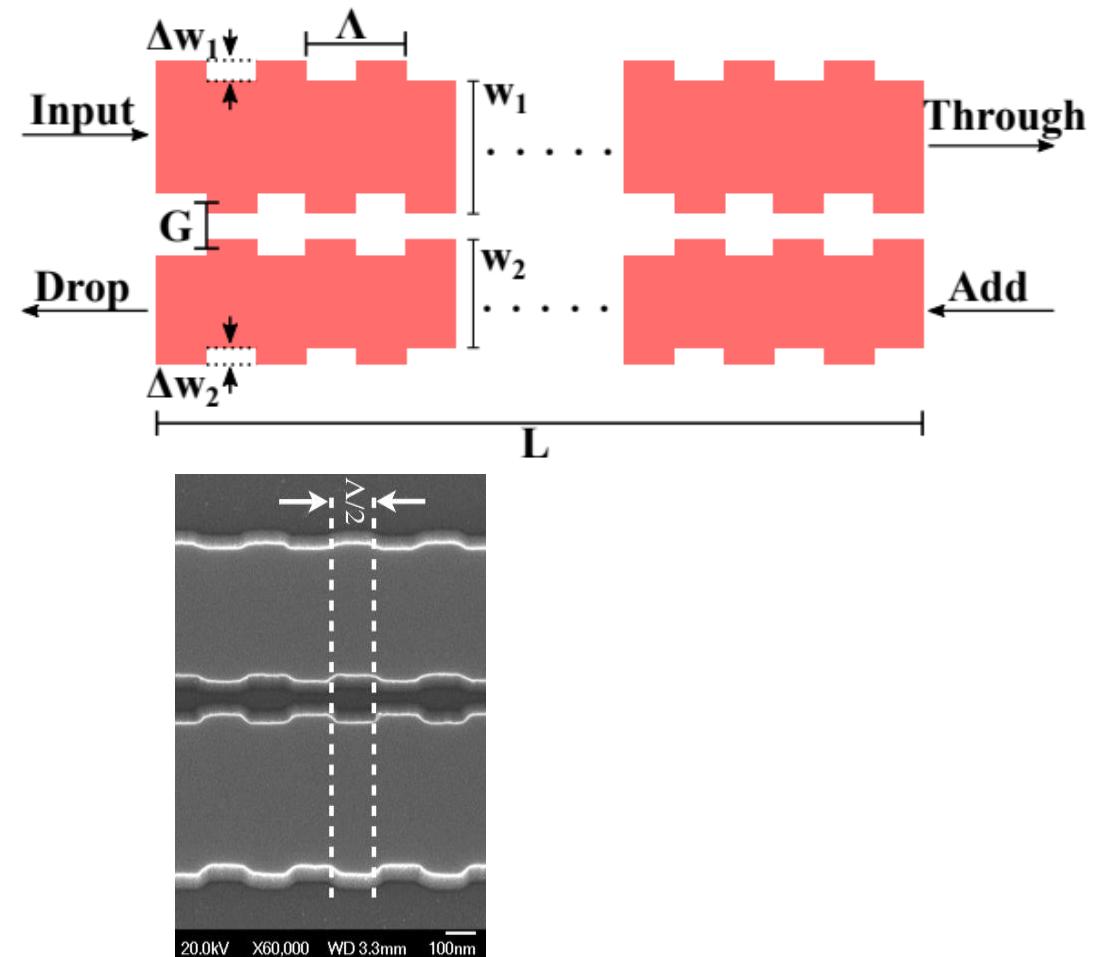
# CONTRA-DIRECTIONAL COUPLERS

- **2-waveguides system, 4-port Device:**
  - Input, Through, Add, Drop
  - Asymmetric waveguides to reduce forward coupling
  - Light at the phase-matched wavelengths couples backwards into the second waveguide (contra)



# CONTRA-DIRECTIONAL COUPLERS

- **Design parameters:**
  - Waveguides widths, corrugations width, waveguides gap, corrugations period apodization profile
- Selected design parameters determine the **figures of merit:**
  - Bandwidth, central wavelength, band ripple/flatness, crosstalk
- Demonstrated on both E-Beam Deep-Ultraviolet (DUV) lithography **[3]**.
- Demonstrated on both C-Band and O-Band.



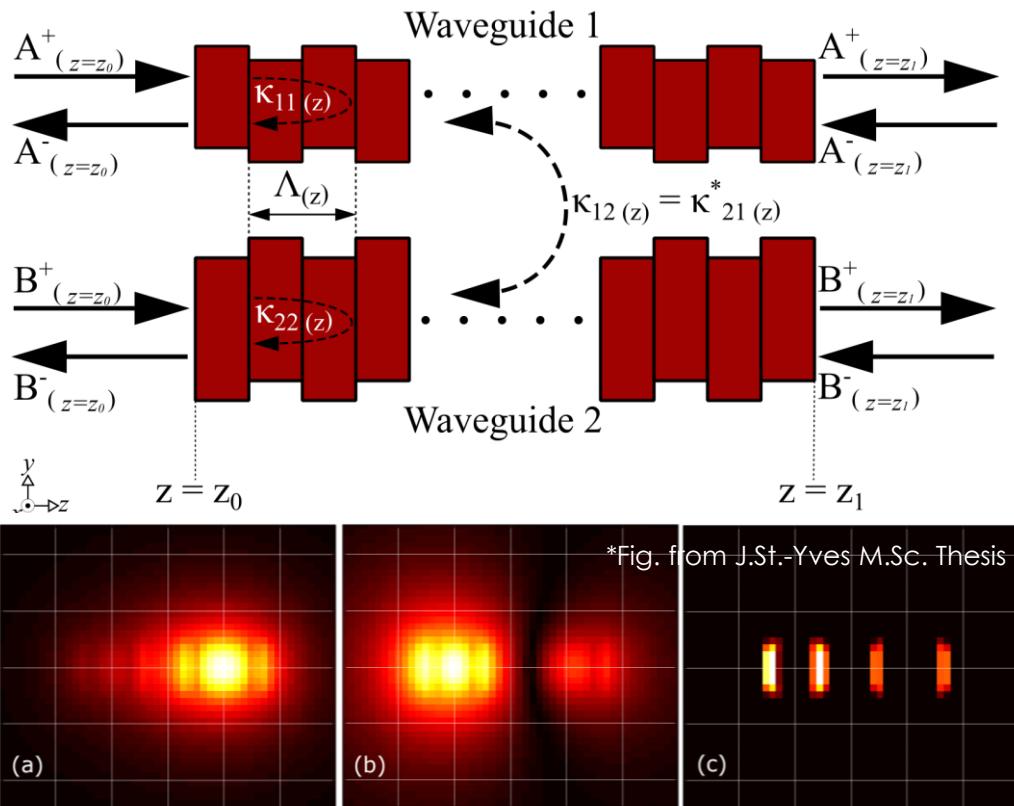
**[3]** W. Shi, X. Wang, W. Zhang, L. Chrostowski, and N. A. F. Jaeger, "Contradirectional couplers in silicon-on-insulator rib waveguides," *Optics Letters*, vol. 36, no. 20, p. 3999, May 2011.

# THEORY & PHOTONIC BAND DIAGRAMS



# CONTRA-DIRECTIONAL COUPLERS

- Coupled-mode theory, Transfer-Matrix method



$$\mathbf{E}(x, y, z) = [A^+(z)e^{-j\widehat{\beta}_1 z} + A^-(z)e^{j\widehat{\beta}_1 z}] \mathbf{E}_1(x, y) + [B^+(z)e^{-j\widehat{\beta}_2 z} + B^-(z)e^{j\widehat{\beta}_2 z}] \mathbf{E}_2(x, y)$$

$$\frac{dA^+}{dz} = -j\kappa_{11}A^-e^{j2\Delta\widehat{\beta}_1 z} - j\kappa_{12}B^-e^{j(\Delta\widehat{\beta}_1 + \Delta\widehat{\beta}_2)z}$$

$$\frac{dB^+}{dz} = -j\kappa_{12}A^-e^{j(\Delta\widehat{\beta}_1 + \Delta\widehat{\beta}_2)z} - j\kappa_{22}B^-e^{j2\Delta\widehat{\beta}_2 z}$$

$$\frac{dA^-}{dz} = j\kappa_{11}^*A^+e^{-j2\Delta\widehat{\beta}_1 z} + j\kappa_{12}^*B^+e^{-j(\Delta\widehat{\beta}_1 + \Delta\widehat{\beta}_2)z}$$

$$\frac{dB^-}{dz} = j\kappa_{12}^*A^+e^{-j(\Delta\widehat{\beta}_1 + \Delta\widehat{\beta}_2)z} + j\kappa_{22}^*B^+e^{-j2\Delta\widehat{\beta}_2 z}$$

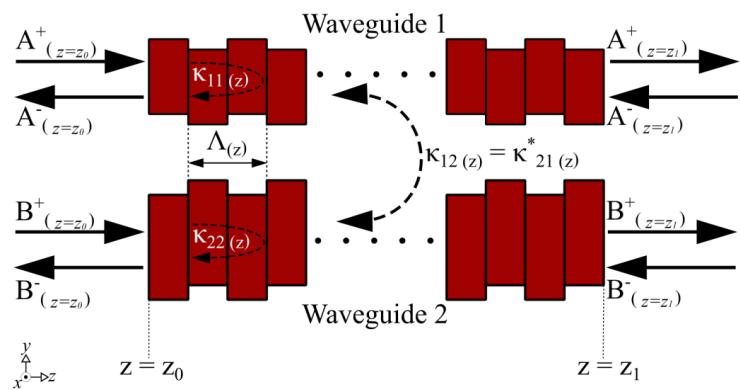
$$\kappa_{11} = \frac{\omega}{4} \iint \mathbf{E}_1^*(x, y) \Delta\epsilon_1(x, y) \mathbf{E}_1(x, y) dx dy$$

$$\kappa_{12} = \kappa_{21}^* = \frac{\omega}{4} \iint \mathbf{E}_1^*(x, y) \Delta\epsilon_1(x, y) \mathbf{E}_2(x, y) dx dy$$

$$\kappa_{22} = \frac{\omega}{4} \iint \mathbf{E}_2^*(x, y) \Delta\epsilon_1(x, y) \mathbf{E}_2(x, y) dx dy$$

# CONTRA-DIRECTIONAL COUPLERS

- Coupled-mode theory, Transfer-Matrix method



$$S_1 = \begin{bmatrix} j\Delta\widehat{\beta}_1 & 0 & 0 & 0 \\ 0 & j\Delta\widehat{\beta}_2 & 0 & 0 \\ 0 & 0 & -j\Delta\widehat{\beta}_1 & 0 \\ 0 & 0 & 0 & -j\Delta\widehat{\beta}_2 \end{bmatrix}$$

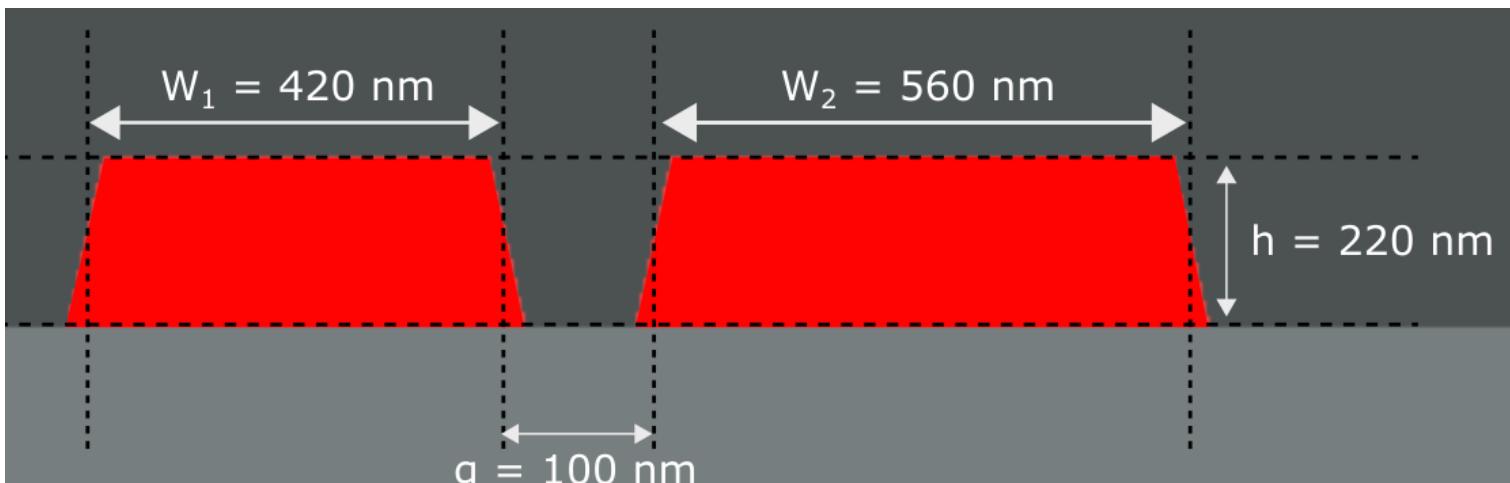
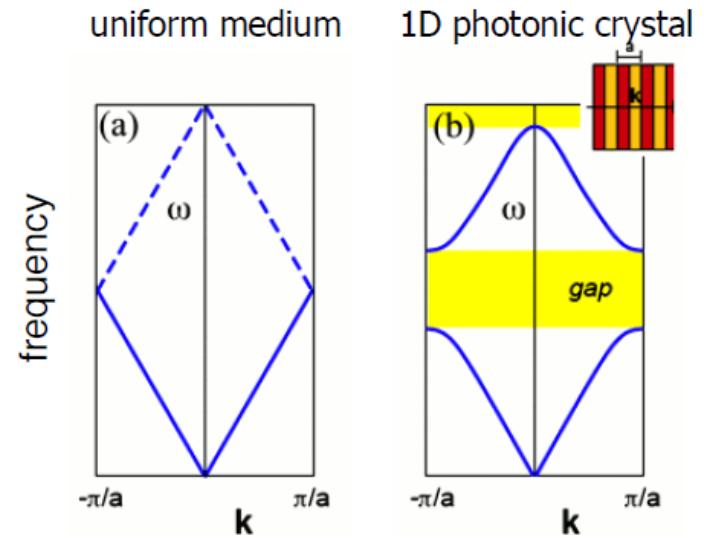
$$S_2 = \begin{bmatrix} -j\Delta\widehat{\beta}_1 & 0 & -j\kappa_{11}e^{j2\Delta\widehat{\beta}_1 z_1} & -j\kappa_{12}e^{j(\Delta\widehat{\beta}_1 + \Delta\widehat{\beta}_2)z_1} \\ 0 & -j\Delta\widehat{\beta}_2 & -j\kappa_{12}e^{j(\Delta\widehat{\beta}_1 + \Delta\widehat{\beta}_2)z_1} & -j\kappa_{22}e^{j2\Delta\widehat{\beta}_2 z_1} \\ j\kappa_{11}^*e^{-j2\Delta\widehat{\beta}_1 z_1} & j\kappa_{21}e^{-j(\Delta\widehat{\beta}_1 + \Delta\widehat{\beta}_2)z_1} & j\Delta\widehat{\beta}_1 & 0 \\ j\kappa_{21}^*e^{-j(\Delta\widehat{\beta}_1 + \Delta\widehat{\beta}_2)z_1} & j\kappa_{22}^*e^{-j2\Delta\widehat{\beta}_2 z_1} & 0 & j\Delta\widehat{\beta}_2 \end{bmatrix}$$

$$E(z) = \begin{bmatrix} A^+(z) \\ B^+(z) \\ A^-(z) \\ B^-(z) \end{bmatrix} \quad E(z_0) = C(z_0, z_1)E(z_1)$$

$$C(z_0, z_1) = e^{S_1(z_1 - z_0)}e^{S_2(z_1 - z_0)}$$

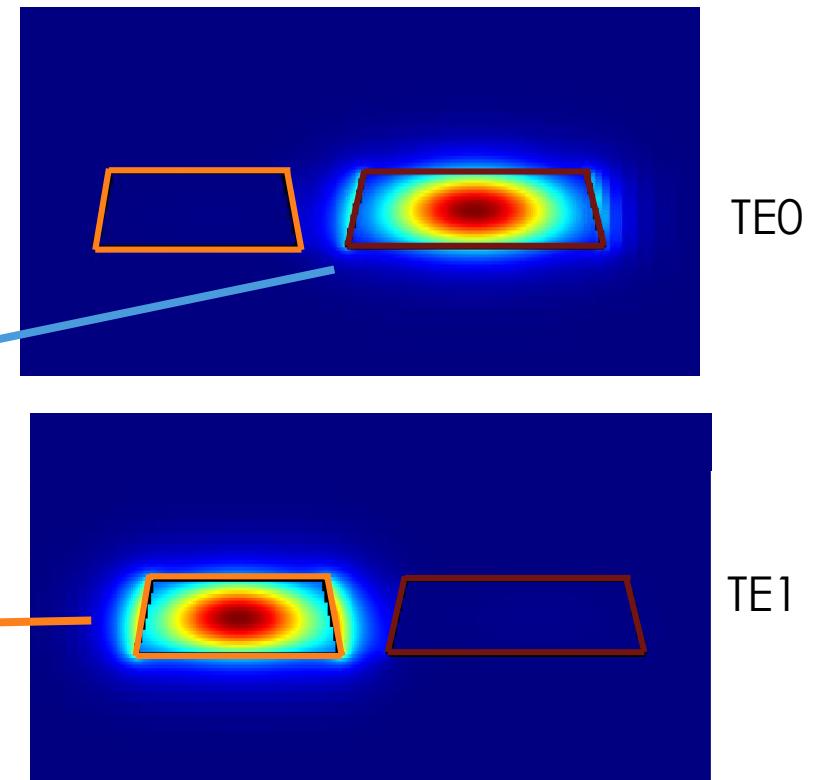
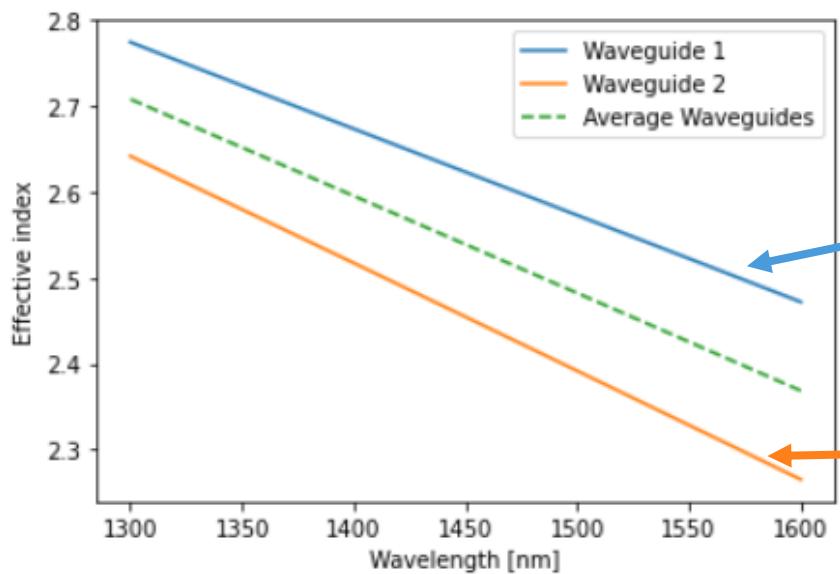
# PHOTONIC BAND DIAGRAMS

- For a single 1-D periodic structure, the degenerate  $k = \pi/\Lambda$  plane waves of a uniform medium are split into standing waves by a dielectric periodicity, forming the lower and upper edges of the band gap.
- Cross section of a two-waveguide system:

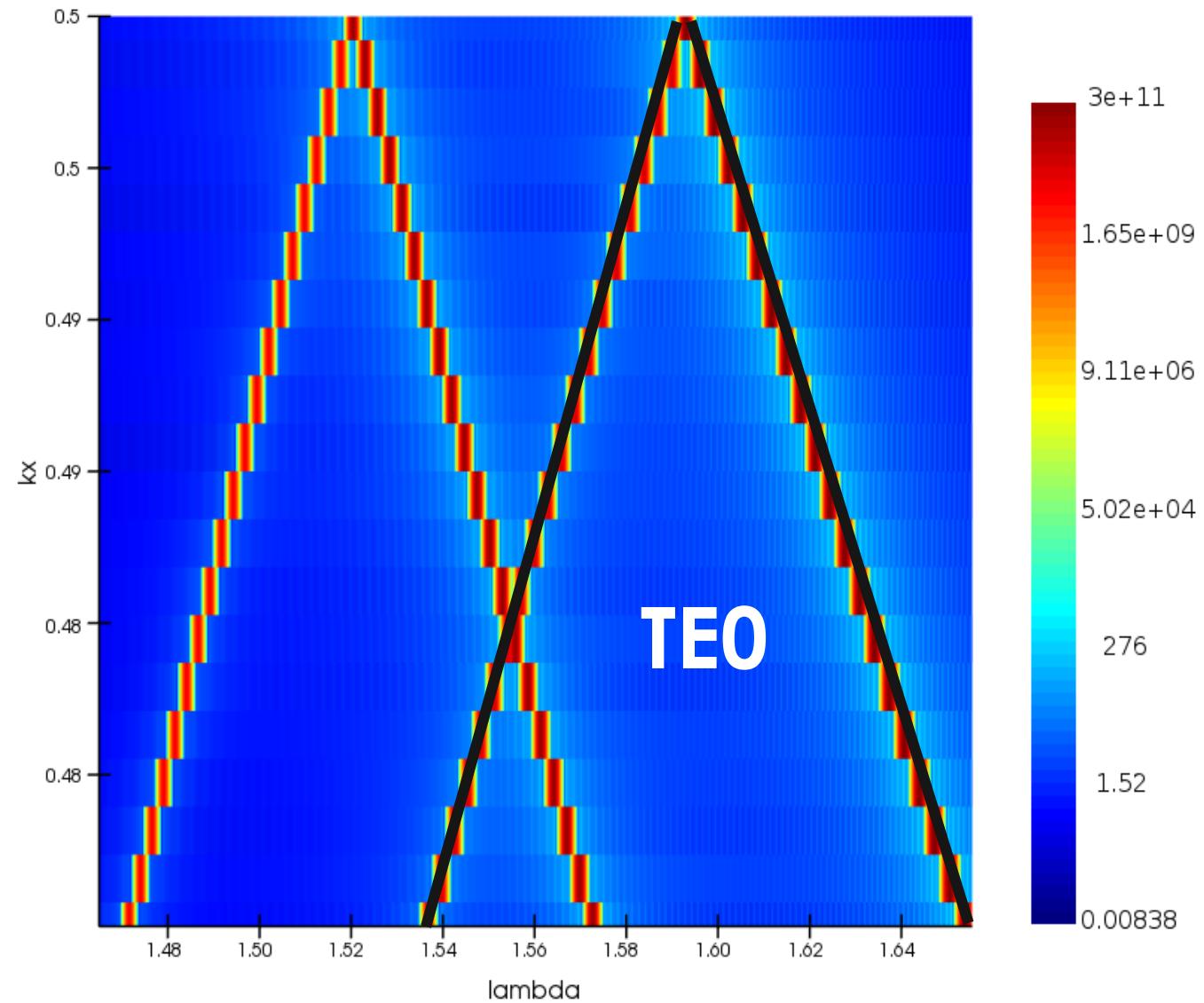
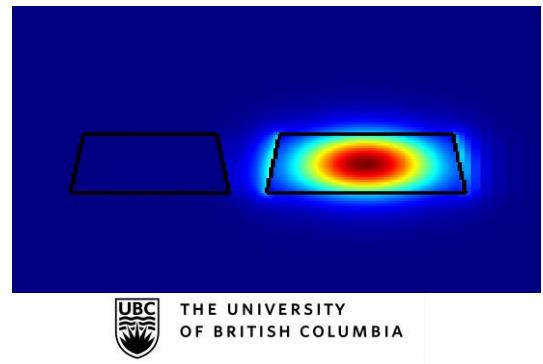


# PHOTONIC BAND DIAGRAMS

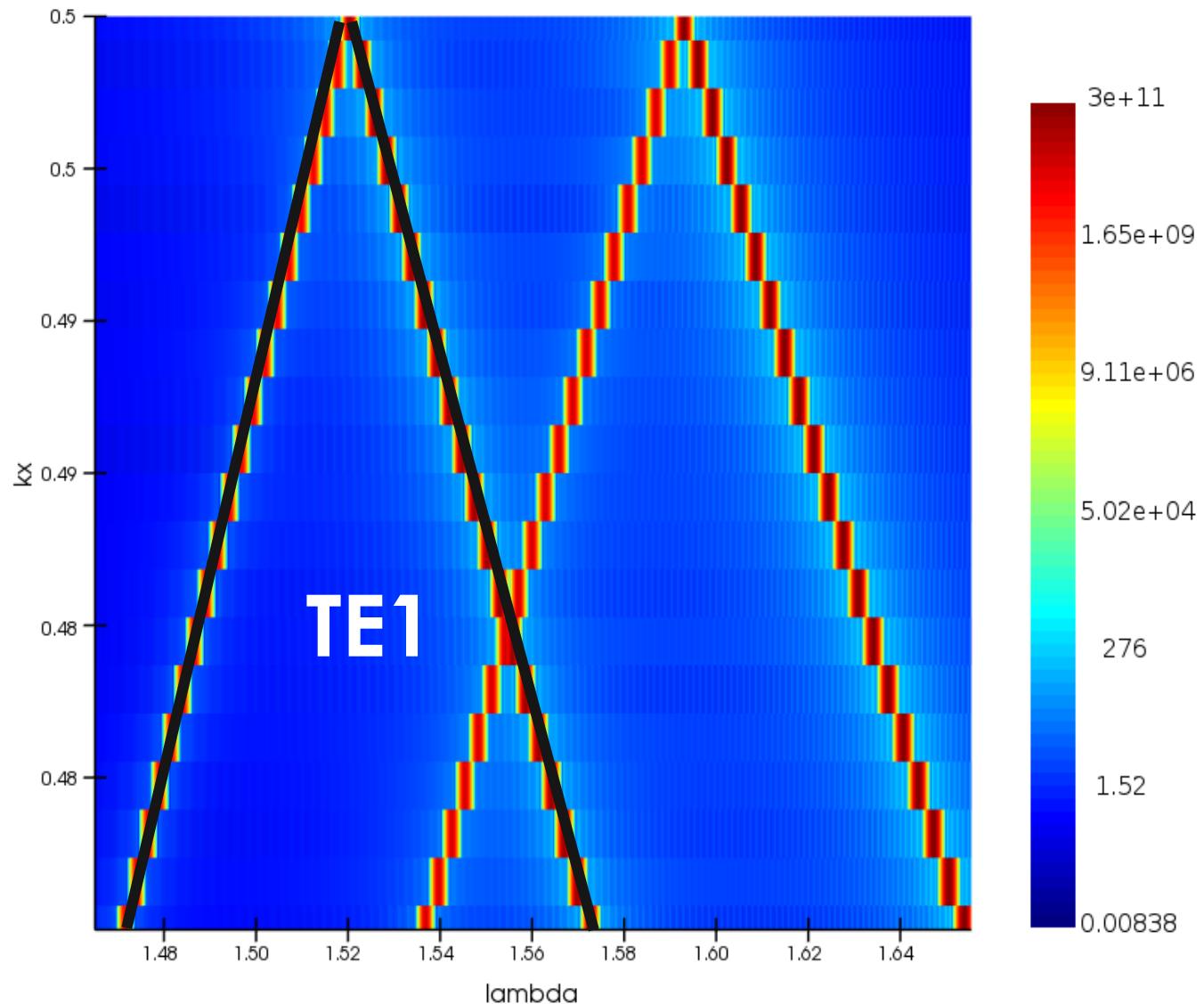
- Dispersion and waveguide compact modes:



# PHOTONIC BAND DIAGRAMS



# PHOTONIC BAND DIAGRAMS



# PHOTONIC BAND DIAGRAMS

## PERTURBING THE SYSTEM

What happens when the waveguides are corrugated periodically?

# PHOTONIC BAND DIAGRAMS

## Unperturbed Waveguides

Waveguide 1



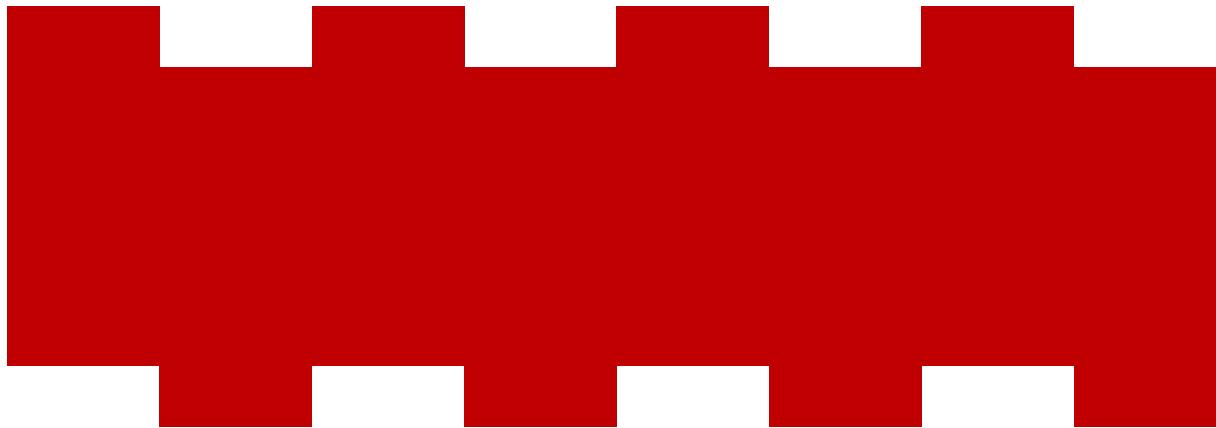
Waveguide 2



# PHOTONIC BAND DIAGRAMS

**perturbed Waveguides**

Waveguide 1



Waveguide 2

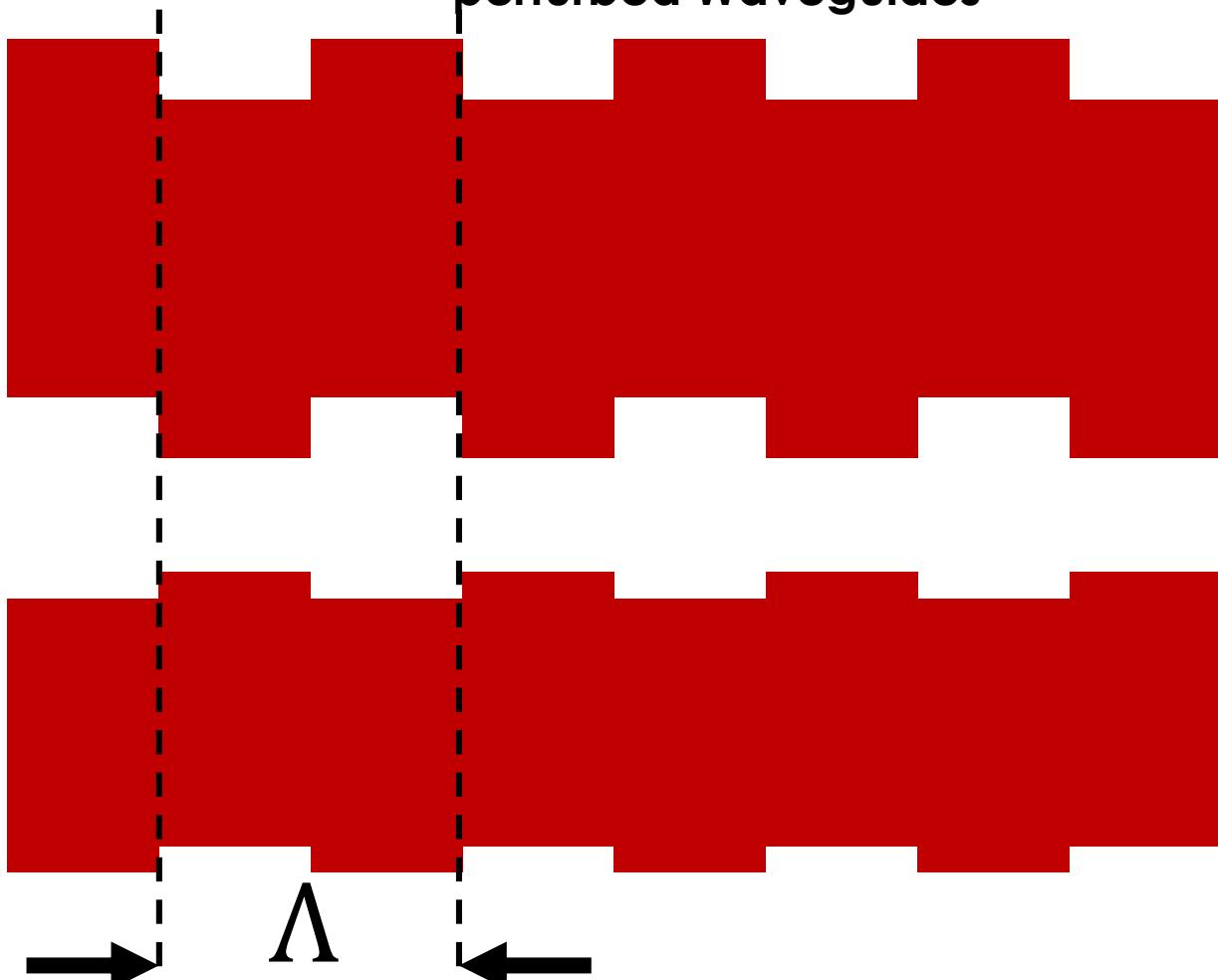


# PHOTONIC BAND DIAGRAMS

Waveguide 1

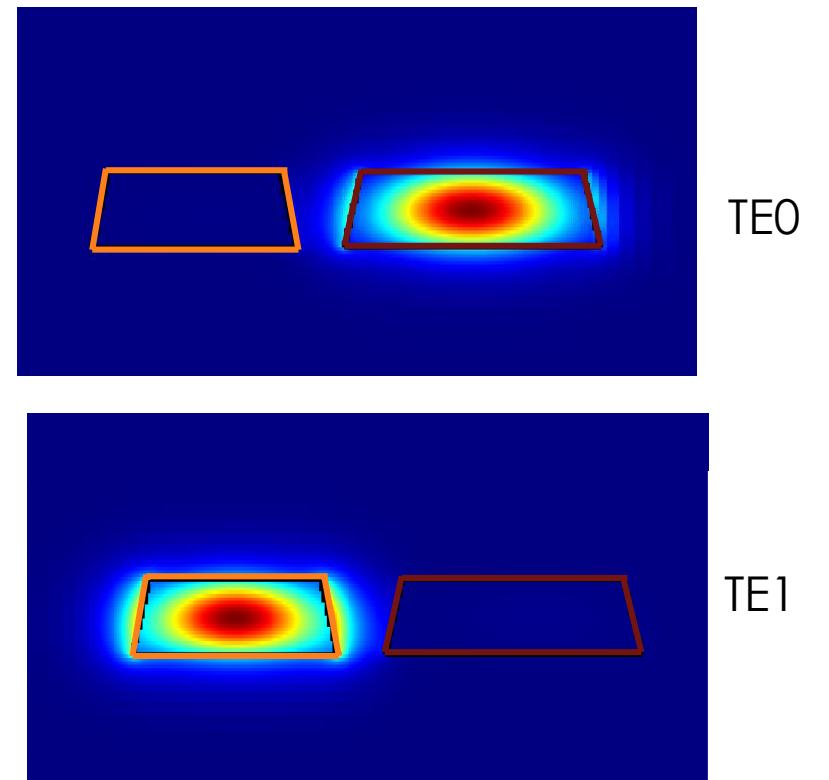
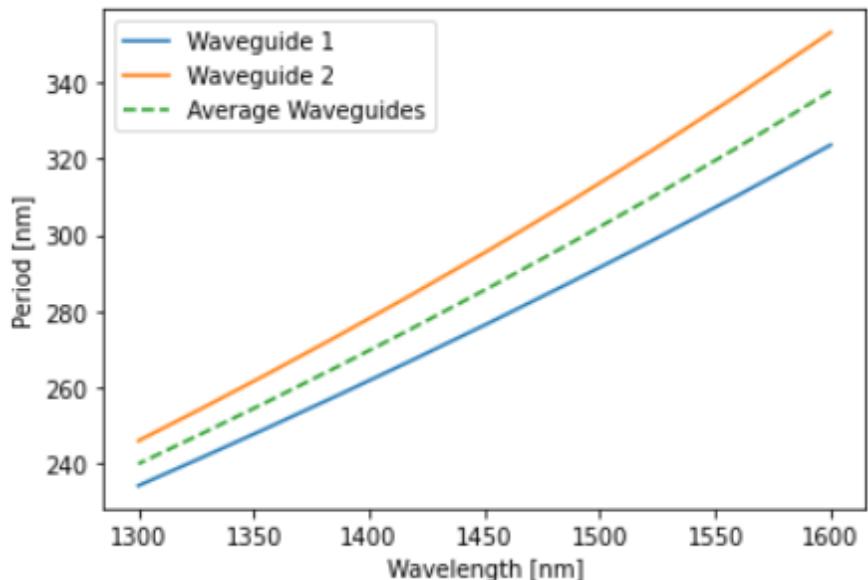
**perturbed Waveguides**

Waveguide 2



# PHOTONIC BAND DIAGRAMS

$$\Lambda = \frac{\lambda}{2 n(\lambda)}$$



# PHOTONIC BAND DIAGRAMS

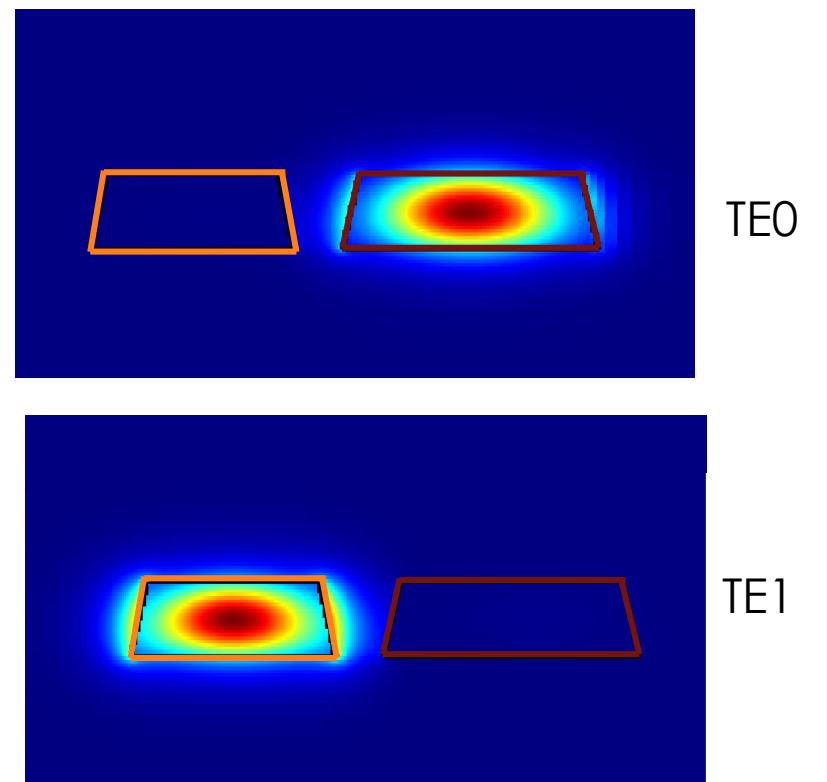
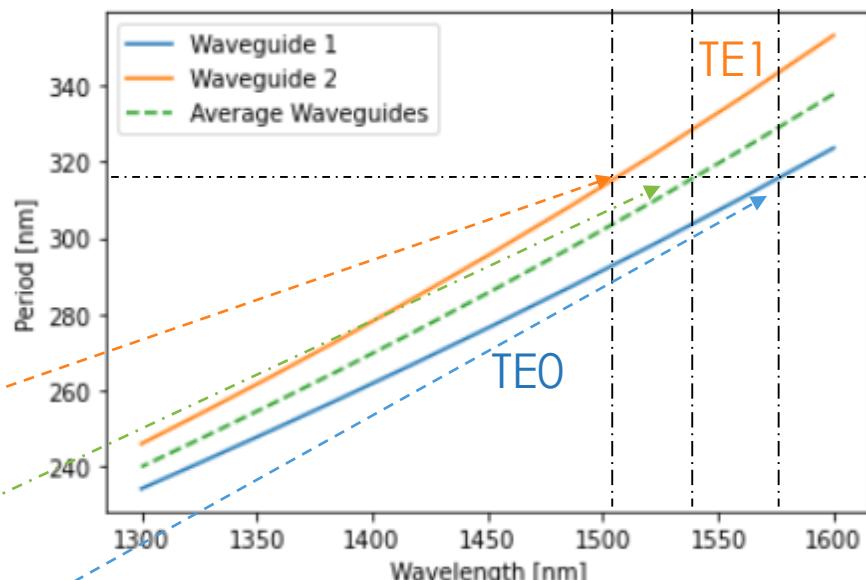
- Designer choice: Pick a perturbation period of  $\Lambda = 318 \text{ nm}$

$$\Lambda = \frac{\lambda}{2 n(\lambda)}$$

$$\lambda_{wg2} = 1511.4 \text{ nm}$$

$$\lambda_{CDC} = 1545.6 \text{ nm}$$

$$\lambda_{wg1} = 1582.9 \text{ nm}$$

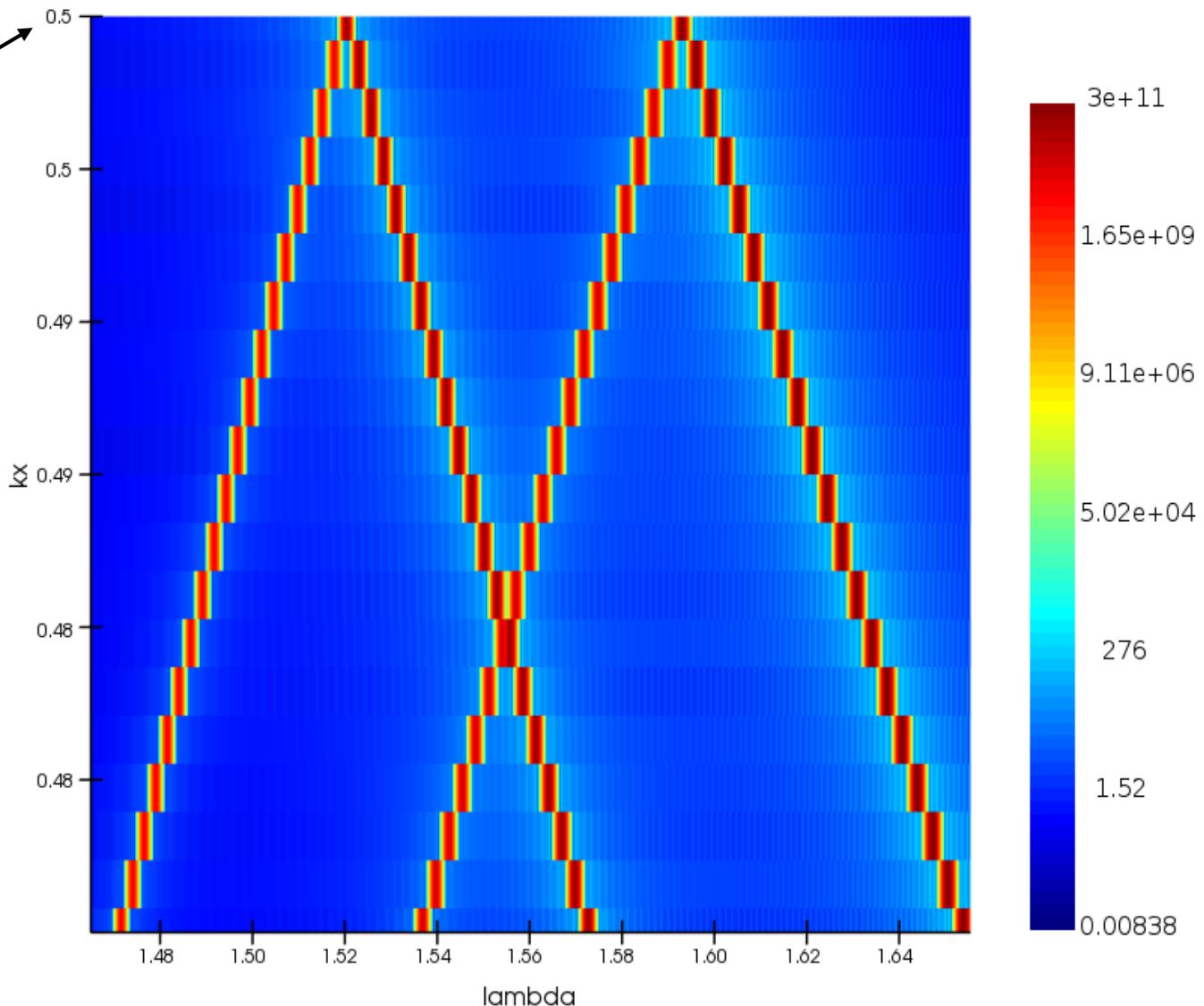


## Unperturbed Waveguides

# PHOTONIC BAND DIAGRAMS

$$k_{x0} = \frac{\pi}{\Lambda} = 0.5$$

$$k_x = \frac{2 \pi n(y)}{\lambda}$$

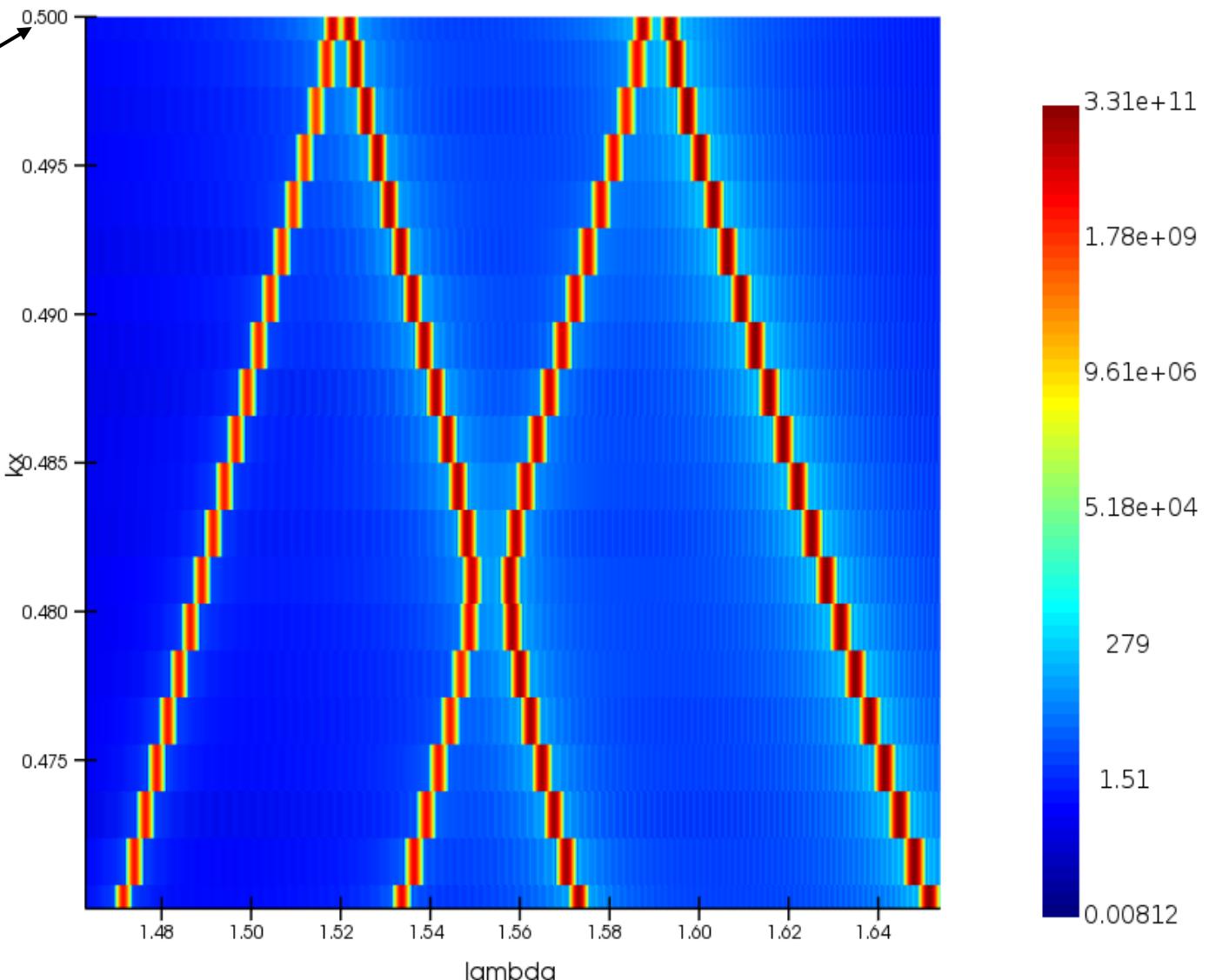


## perturbed Waveguides

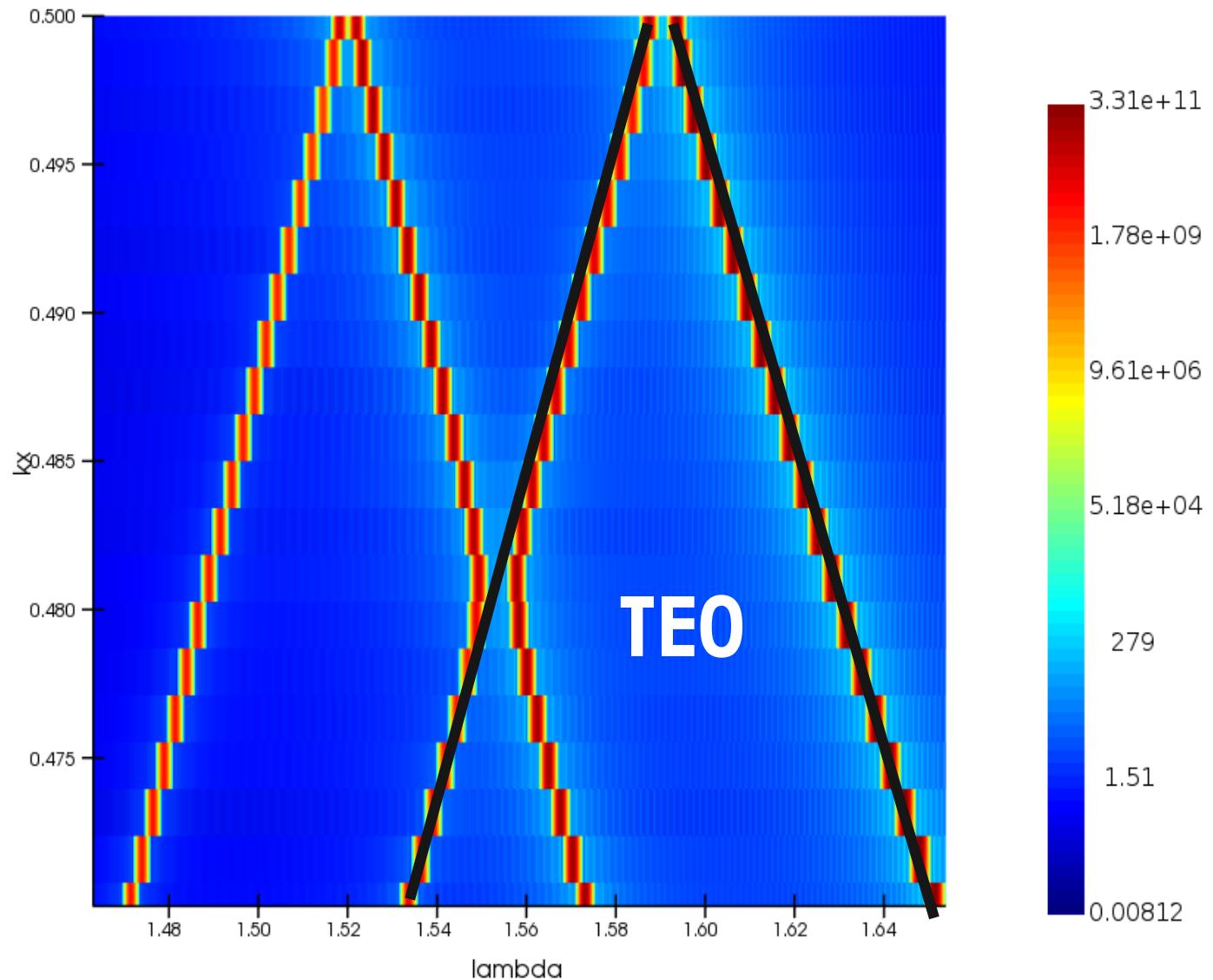
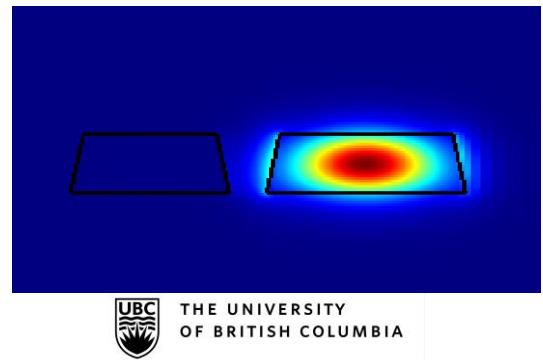
# PHOTONIC BAND DIAGRAMS

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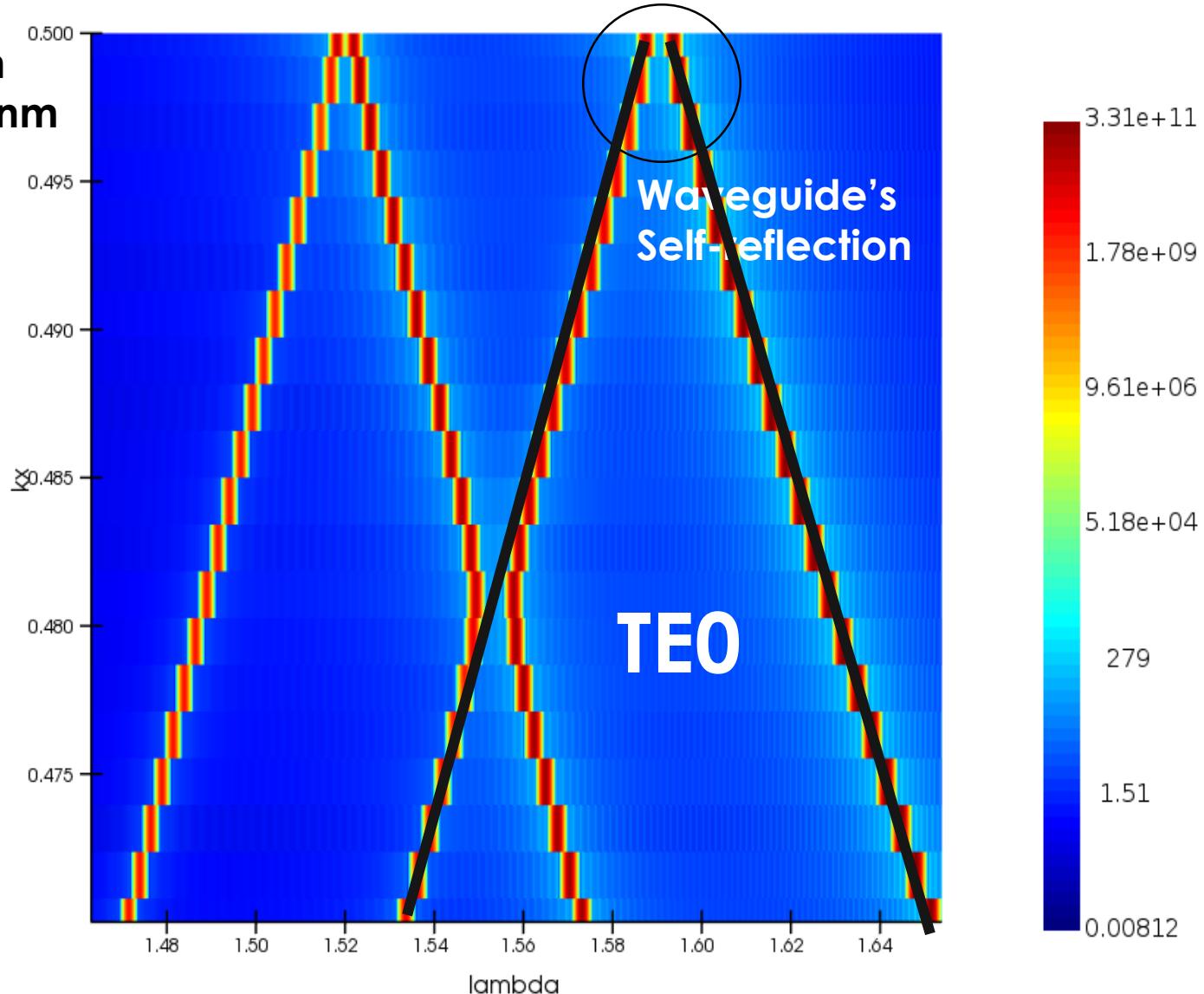
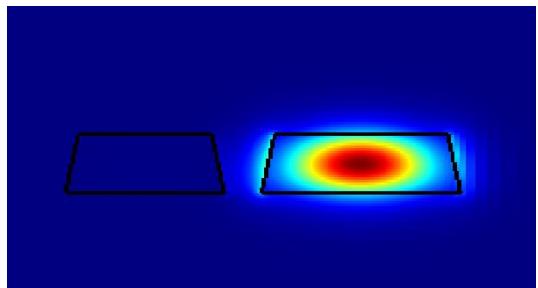
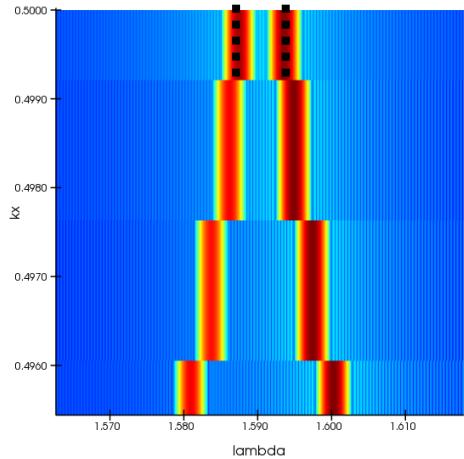


# PHOTONIC BAND DIAGRAMS

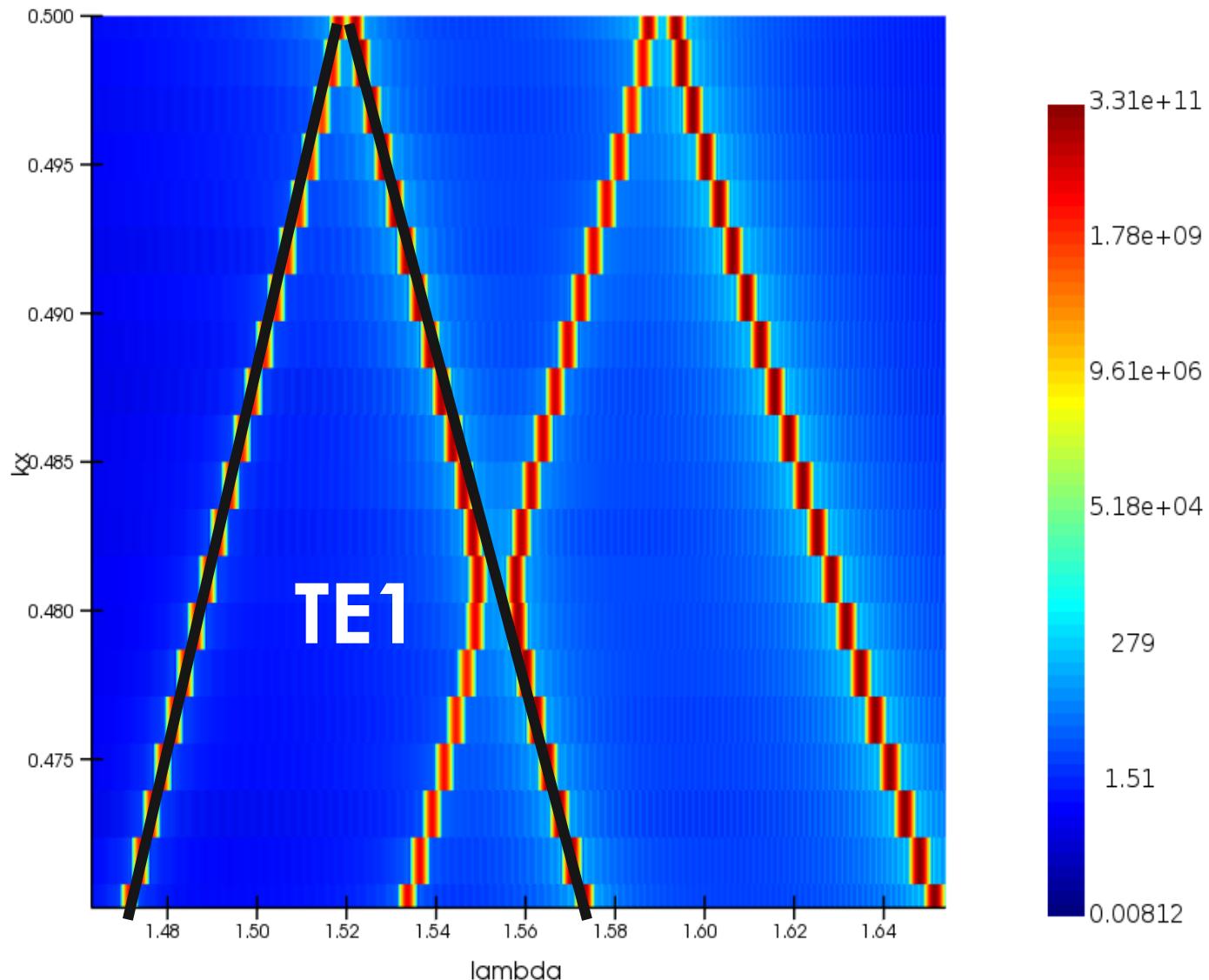


# PHOTONIC BAND DIAGRAMS

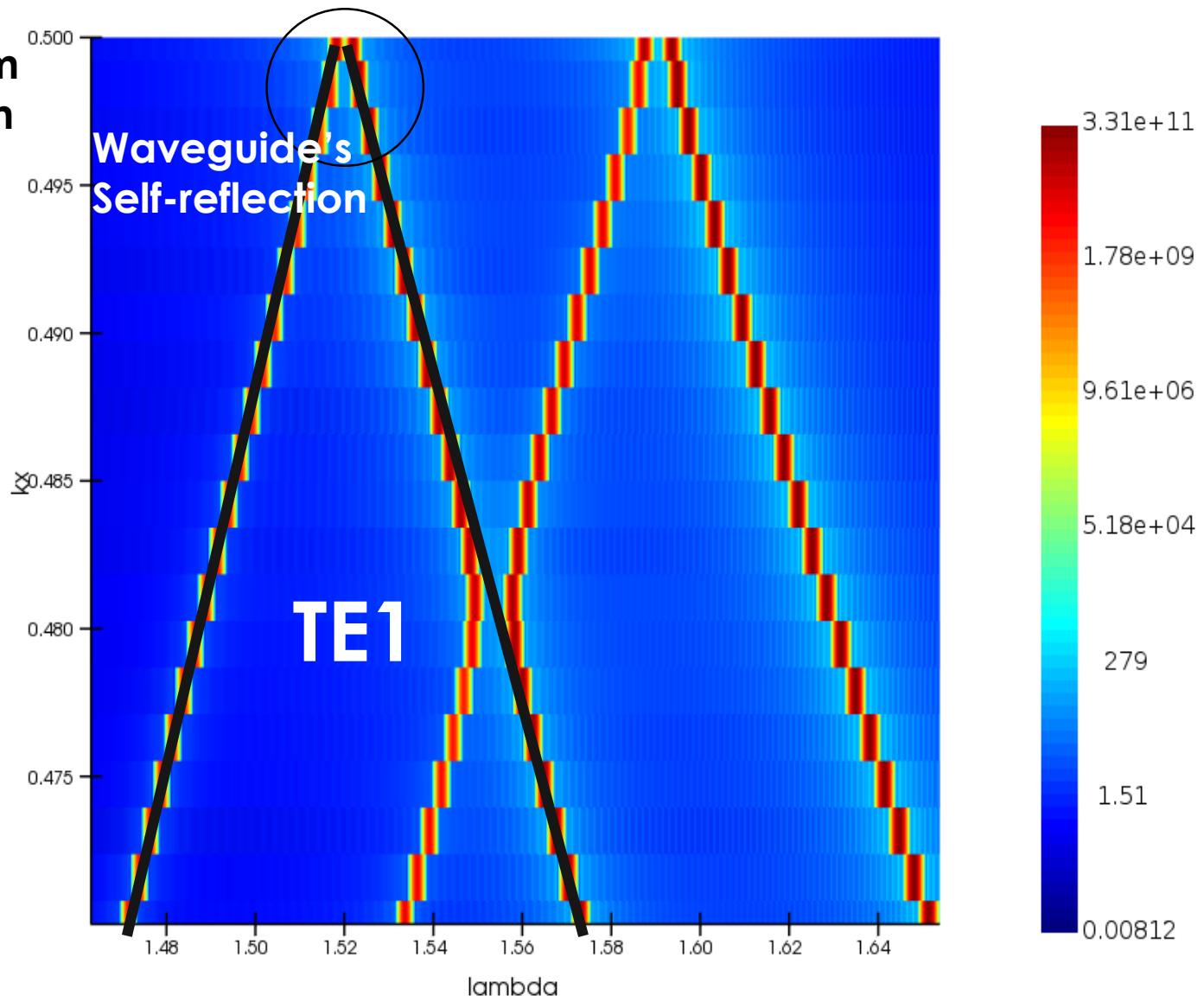
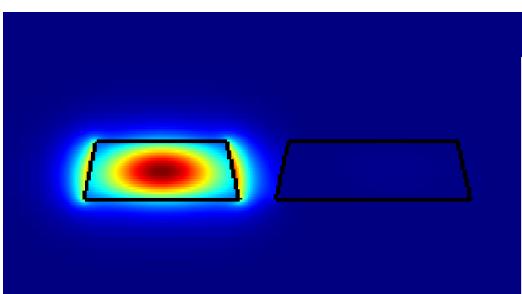
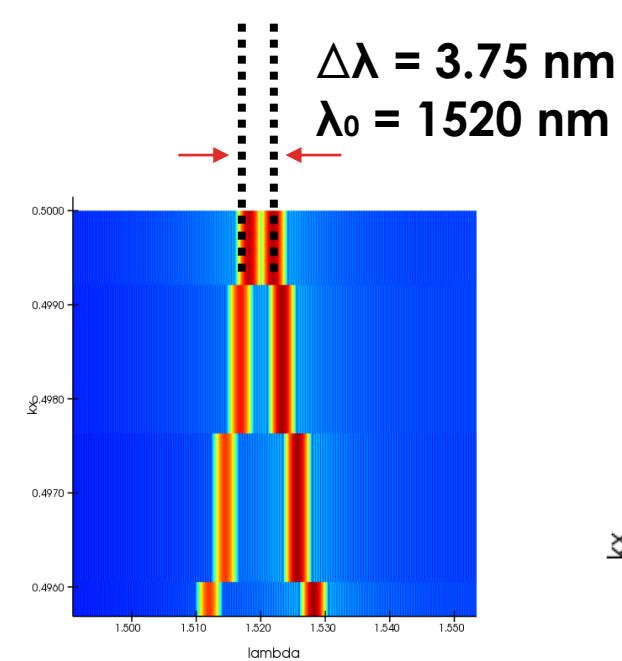
$$\Delta\lambda = 6.2 \text{ nm}$$
$$\lambda_0 = 1590.5 \text{ nm}$$



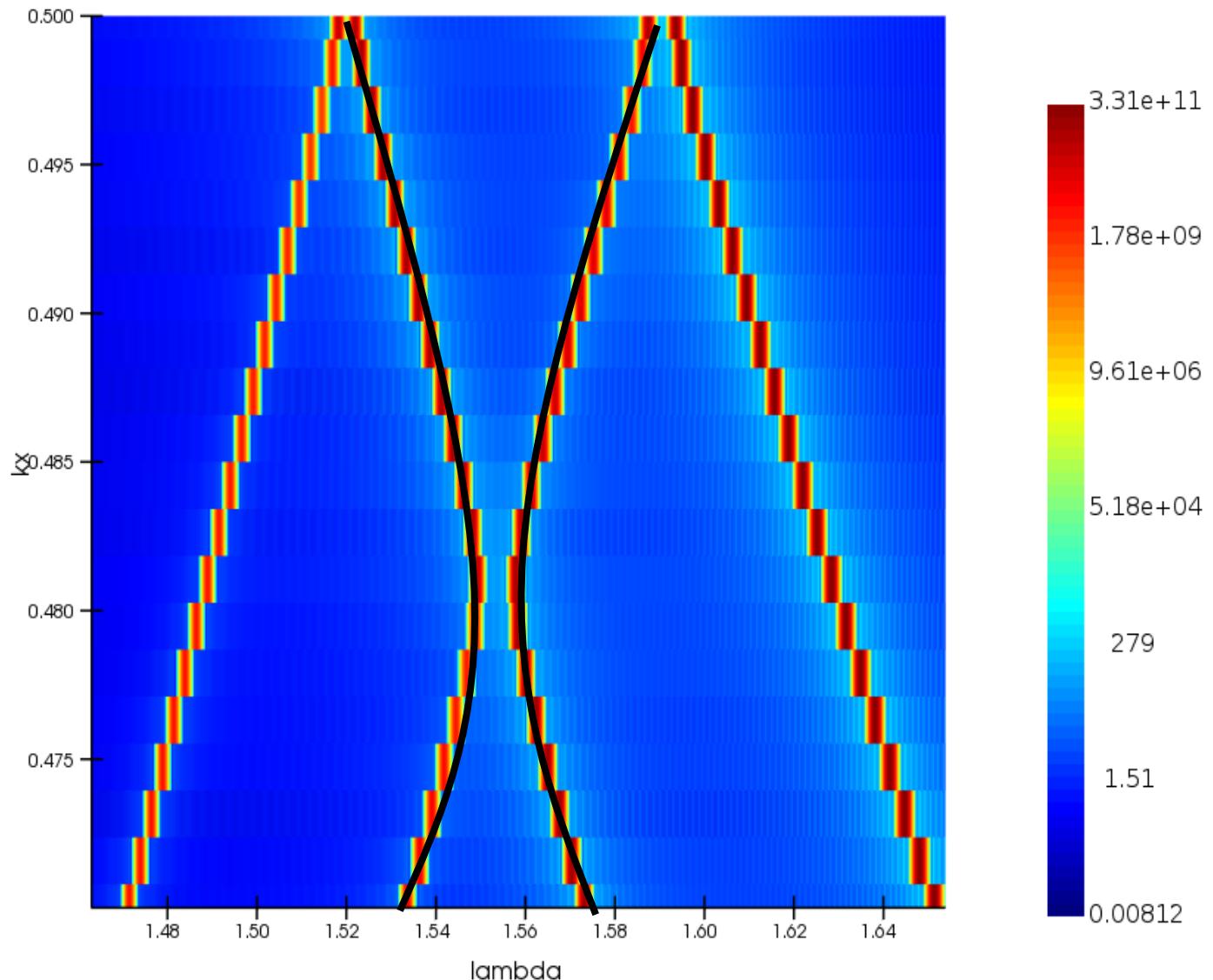
# PHOTONIC BAND DIAGRAMS



# PHOTONIC BAND DIAGRAMS

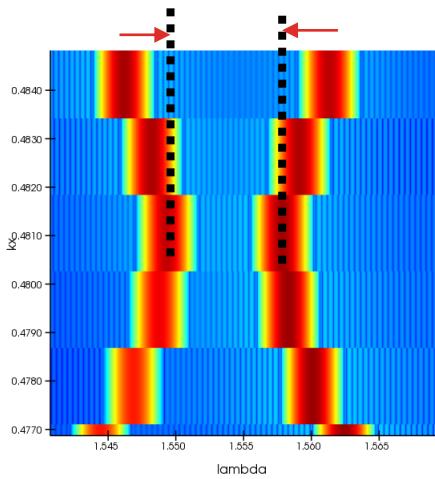


# PHOTONIC BAND DIAGRAMS

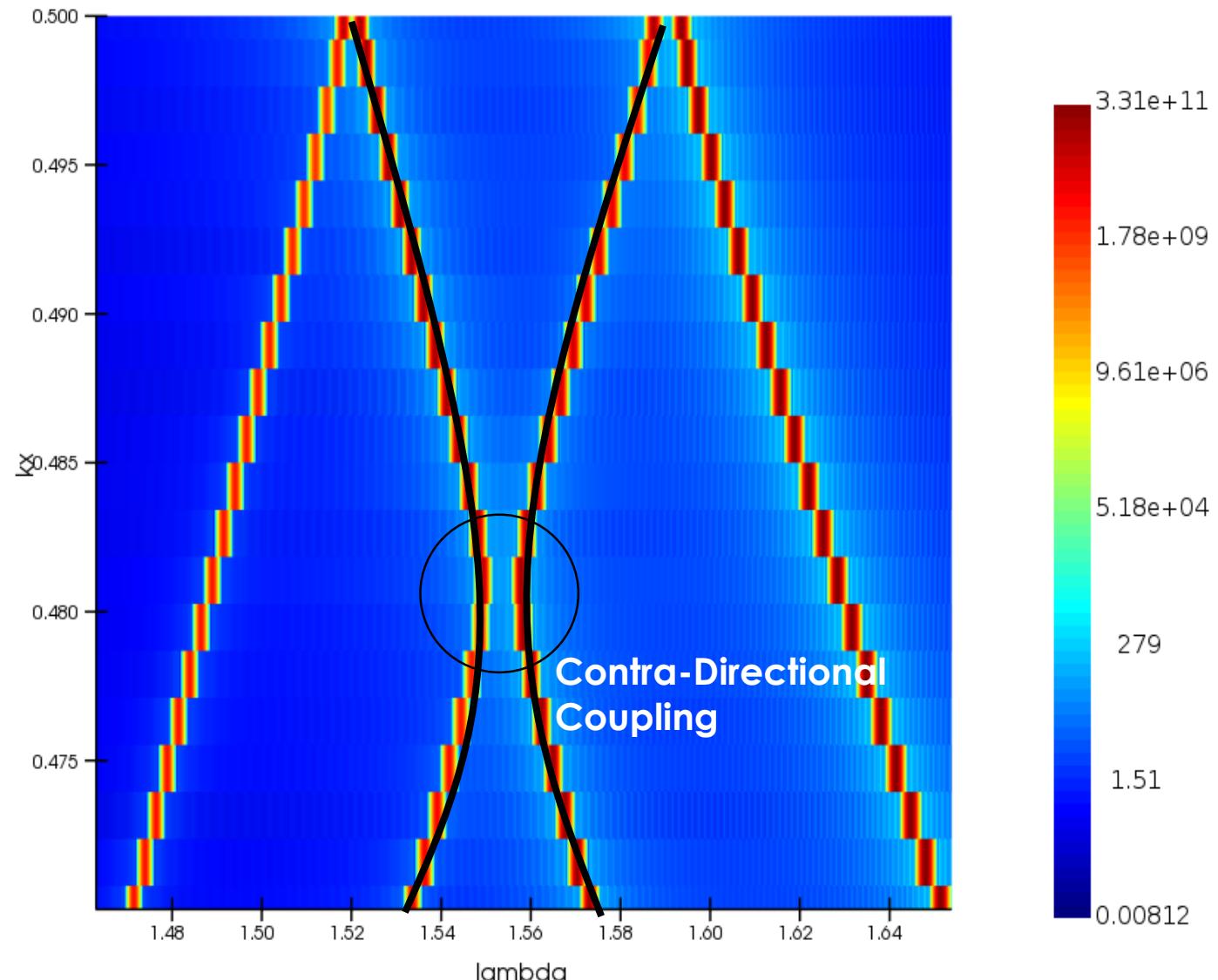


# PHOTONIC BAND DIAGRAMS

$$\Delta\lambda = 8.4 \text{ nm}$$
$$\lambda_0 = 1553.5 \text{ nm}$$

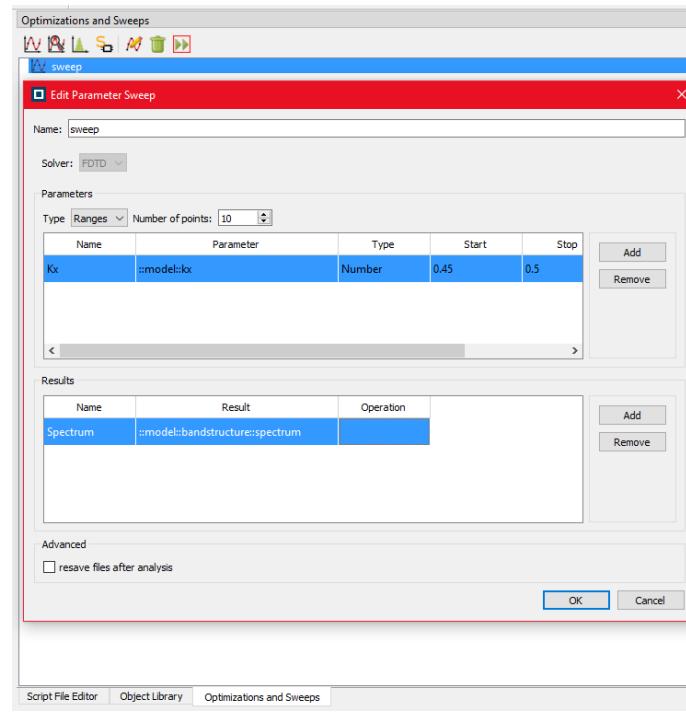
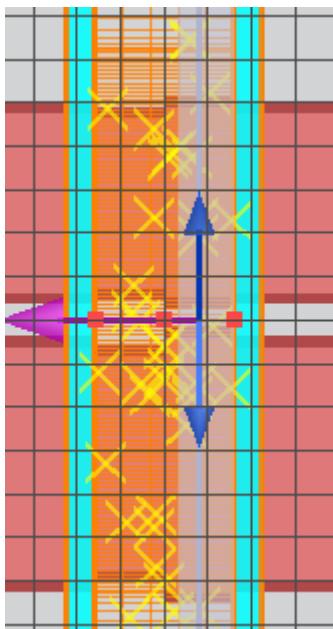


$$\kappa = \pi n_g \Delta\lambda / \lambda_0^2$$



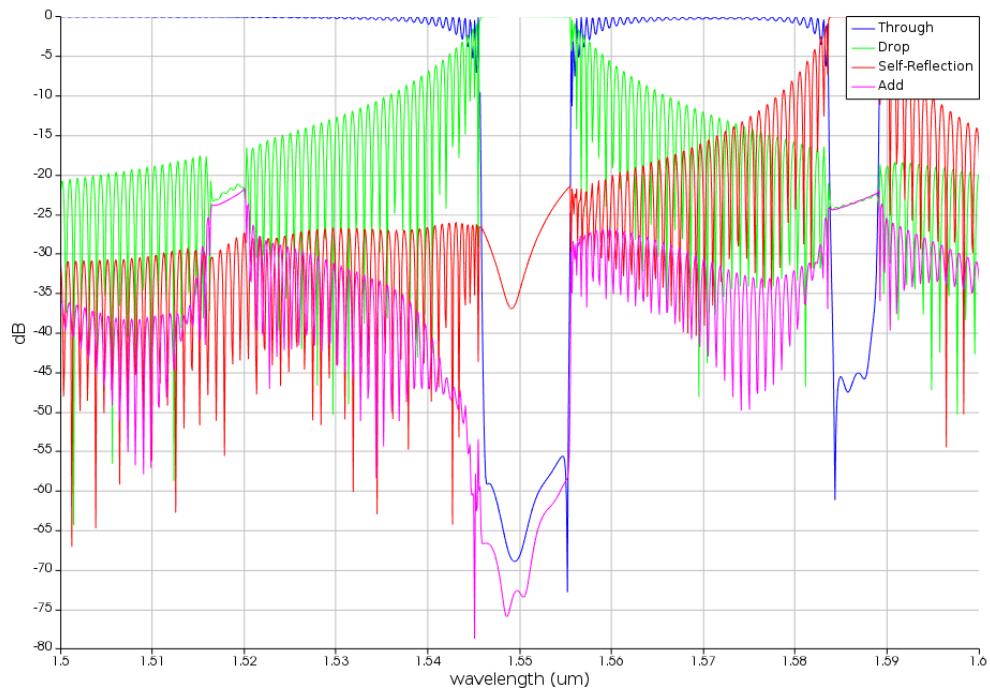
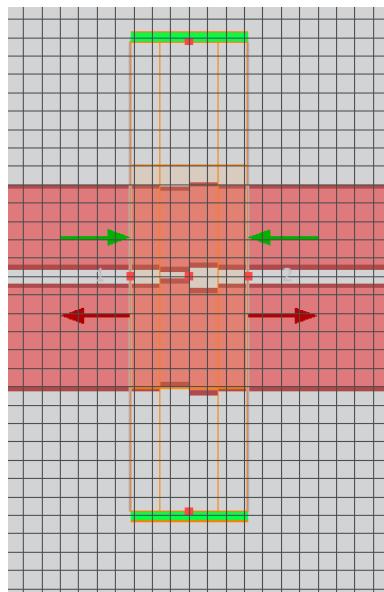
# PHOTONIC BAND DIAGRAMS IN FDTD

- Tutorial available through FDTD -> Bandstructure -> MAIN\_Bandstructure.lsf
- Create a sweep to generate the band diagram after running the script:



# SIMULATE CONTRA-DC IN EME

- Similar to the previously discussed Bragg gratings EME simulations...
- Run EME -> MAIN\_EME.lsf in Lumerical MODE



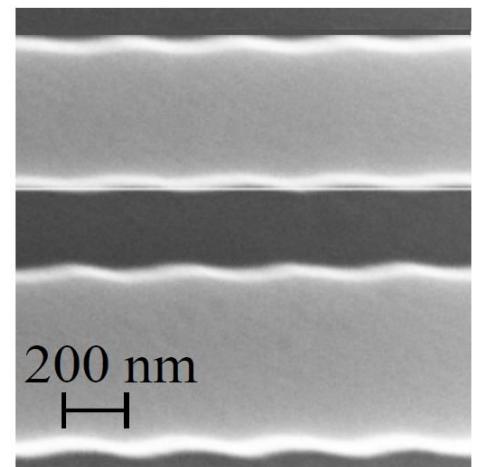
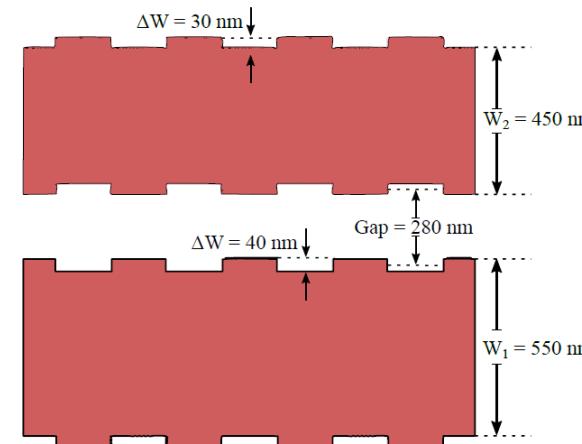
# PRACTICAL DESIGN

Somethings to consider before fabrication...



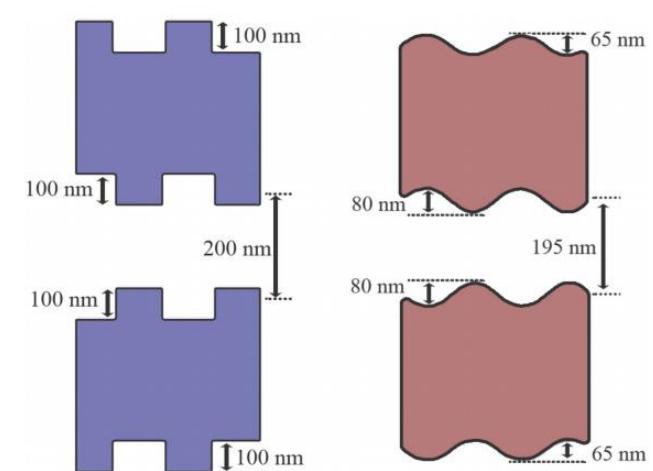
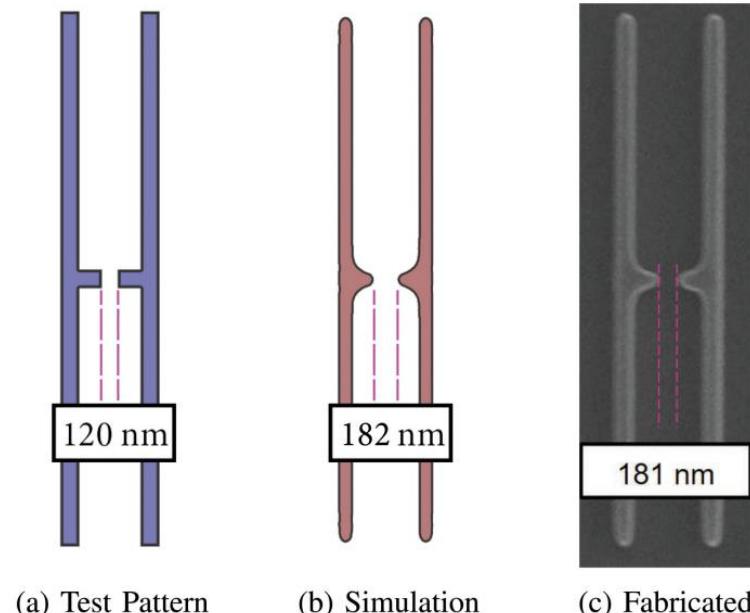
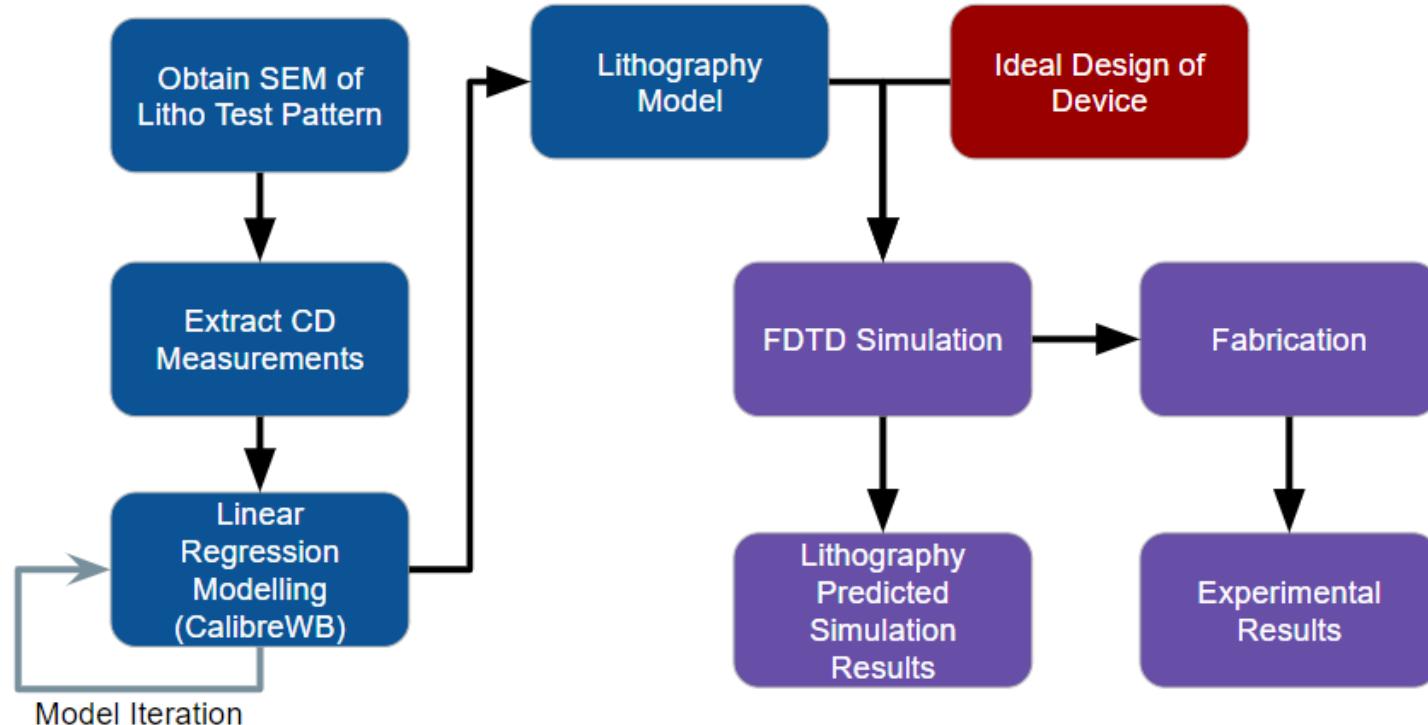
# LITHOGRAPHY EFFECTS

- Low throughput of the electron-beam process makes it unsuitable for large-scale production of photonic devices.
- CMOS-compatible processes, such as deep-ultraviolet (DUV) lithography, have been proven suitable.
- Performance of devices are affected by lithography effects such as smoothing and proximity effects.
- Such effects change the response of a contra-DC significantly, and therefore, must be accounted for prior to fabrication.



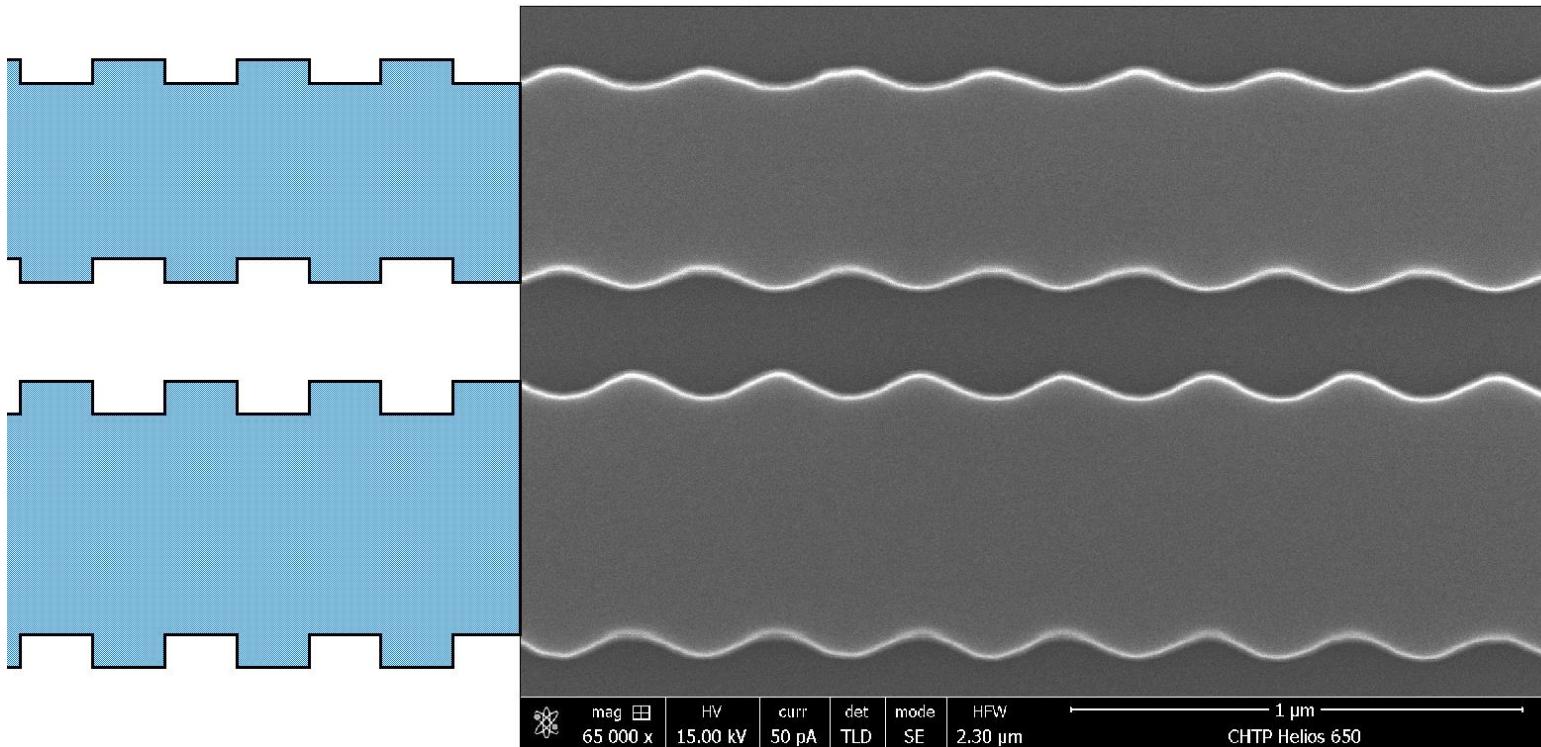
# LITHOGRAPHY EFFECTS

- Lithography effects can be modelled using computational lithography predictive models.



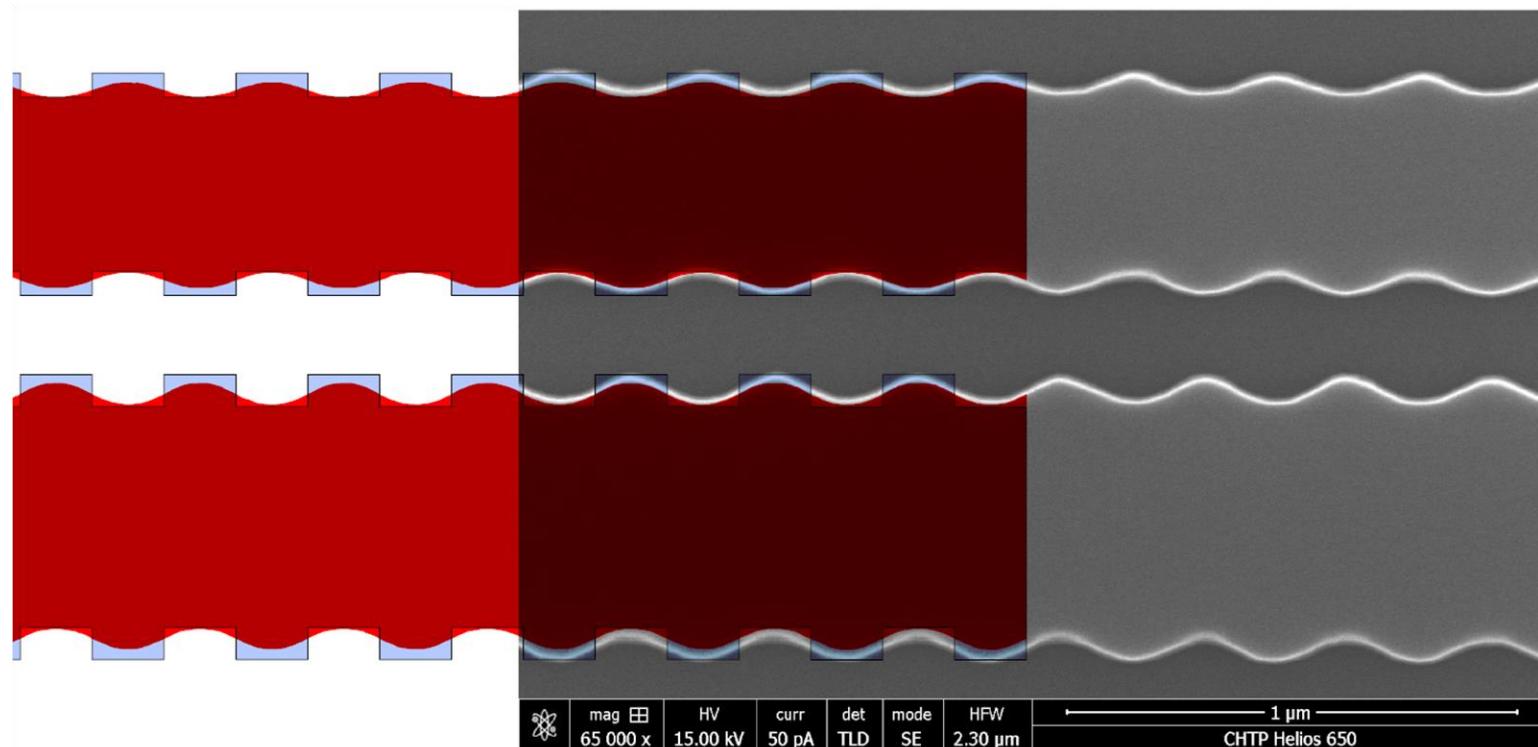
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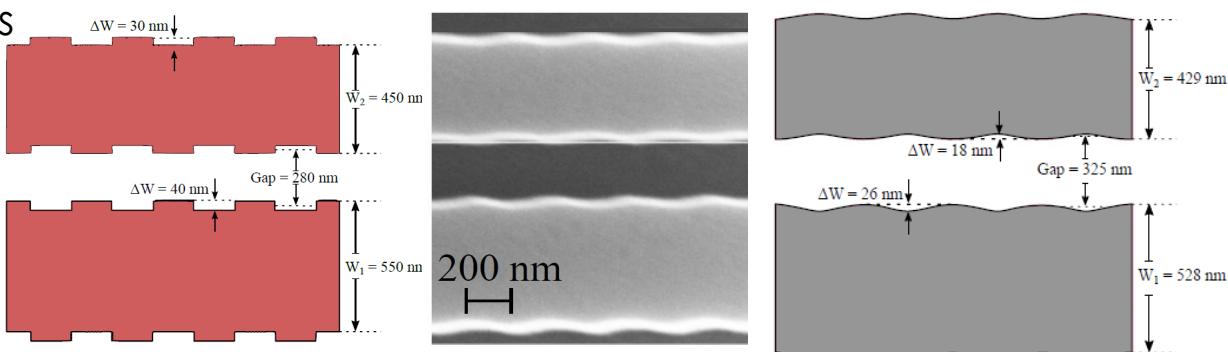
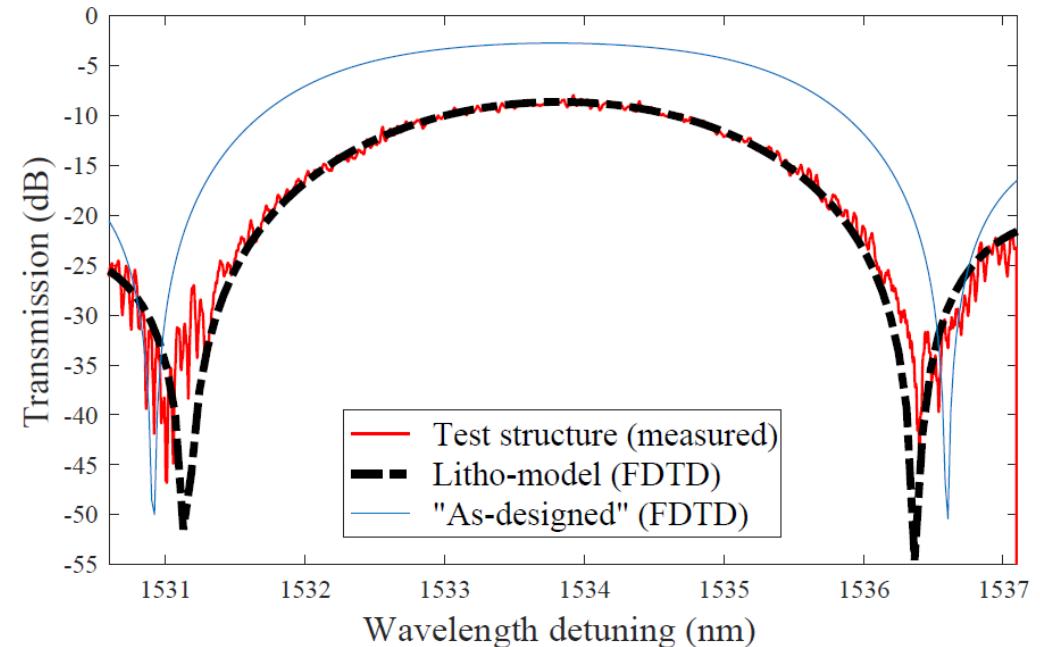
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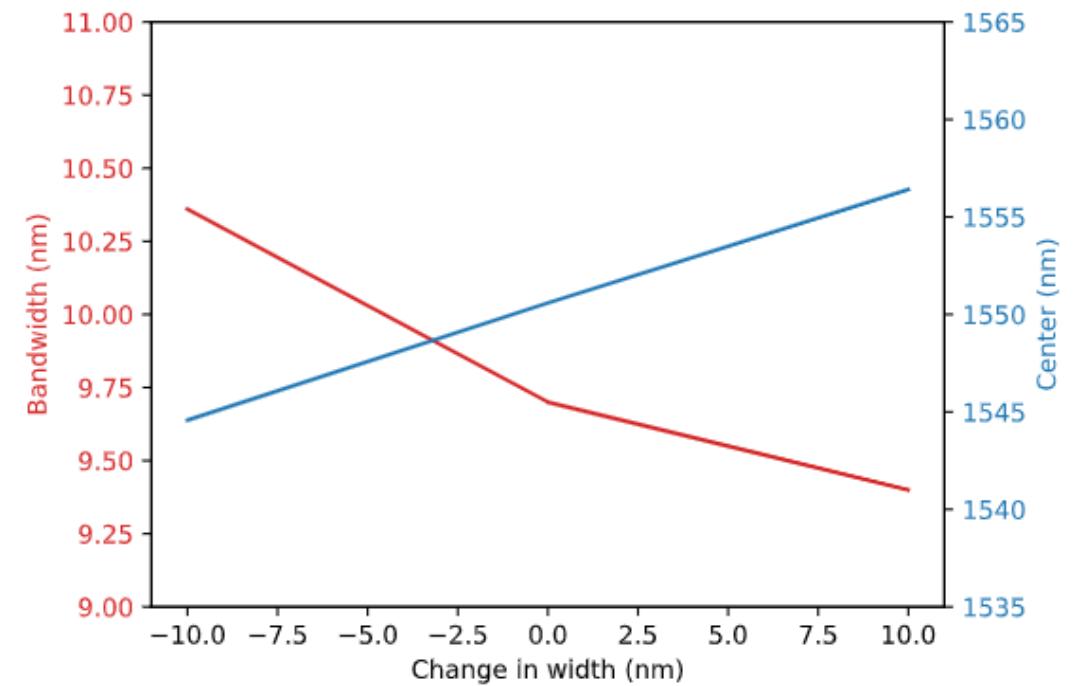
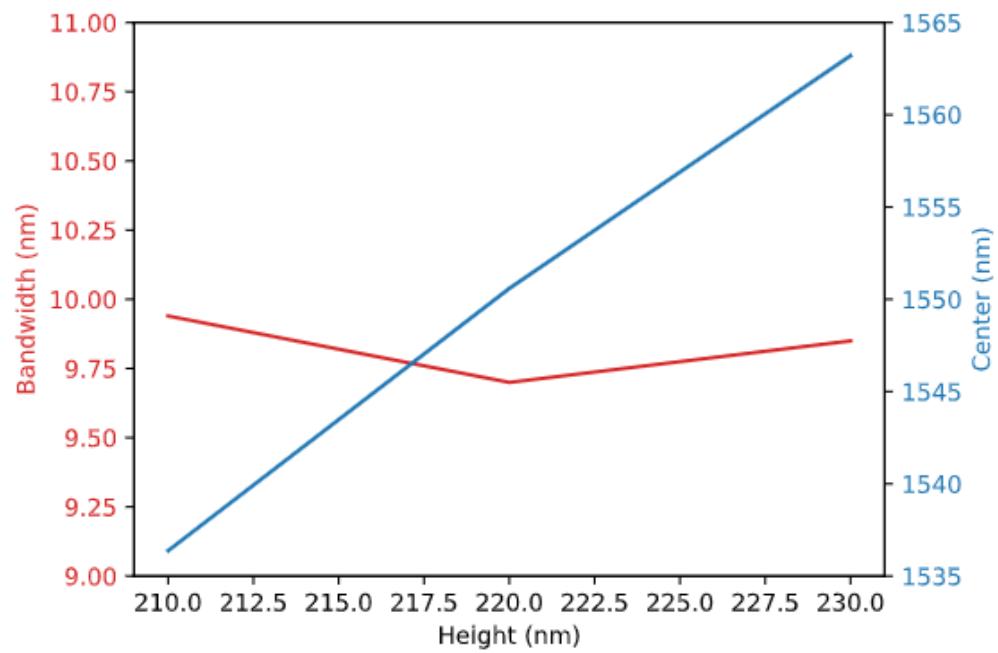
# LITHOGRAPHY EFFECTS

- A reference contra-DC device is designed:
  - Device (ideal) is simulated
  - Device is measured
  - Computational lithography models are applied to predict the fabricated geometry
  - Device (predicted) is simulated
- Knowing predicted device performance allows us to preemptively correct for lithography effects.



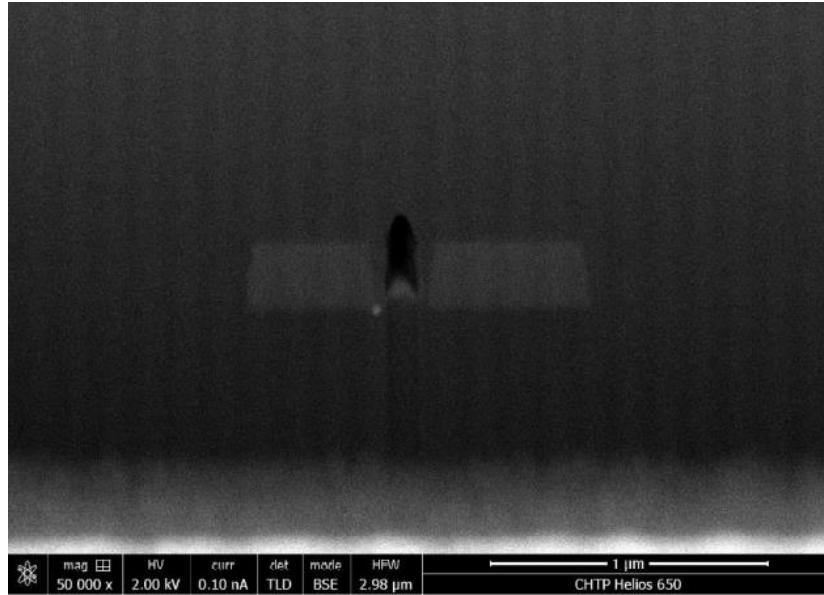
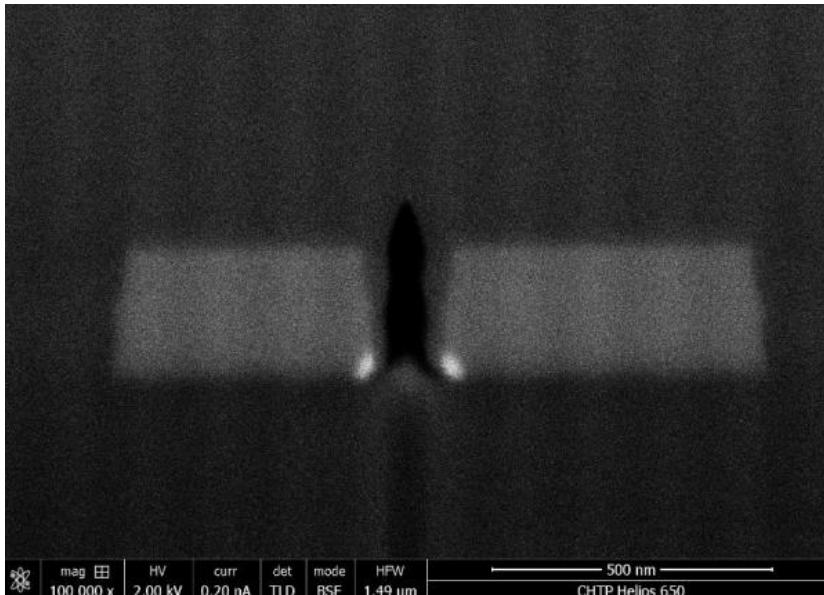
# EFFECTS OF FABRICATION VARIATION

- Changes in device height and width affect the central wavelength and bandwidth
  - How to minimize these affects? How to account for them?



# OTHER EFFECTS TO CONSIDER

- Oxide voids due to non-uniform oxide deposition
  - How to minimize it? Model it?



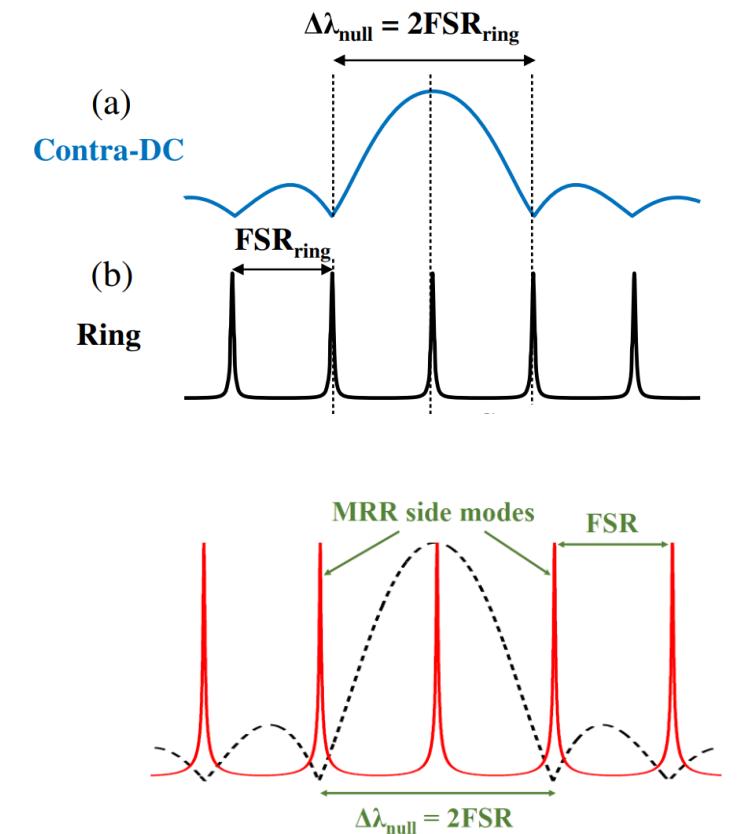
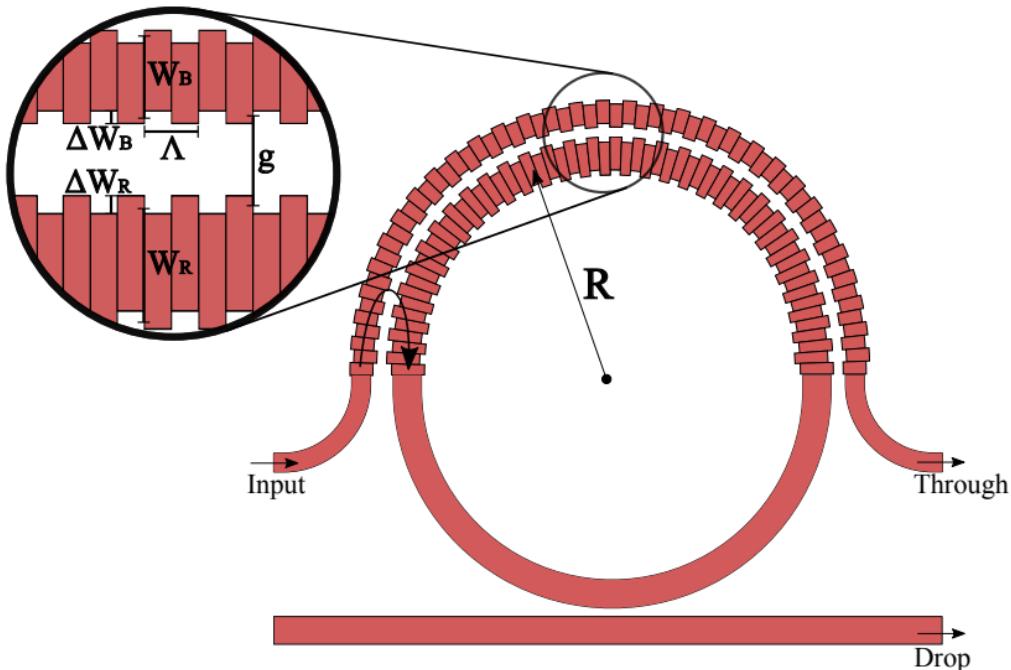
# DESIGNS AND APPLICATIONS

To inspire your next work!



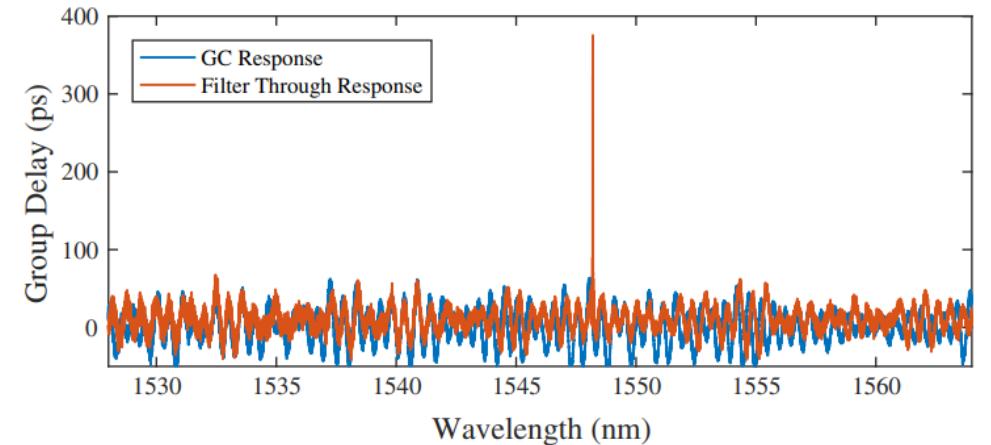
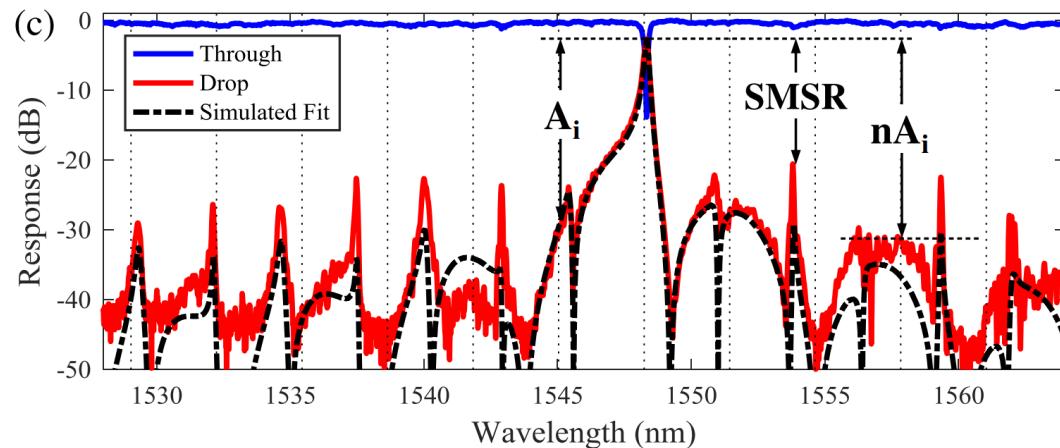
# FSR-FREE RINGS

- Contra-DCs can be integrated into the coupling regions of micro-ring resonators to suppress all the resonances, except those at the Bragg wavelength.



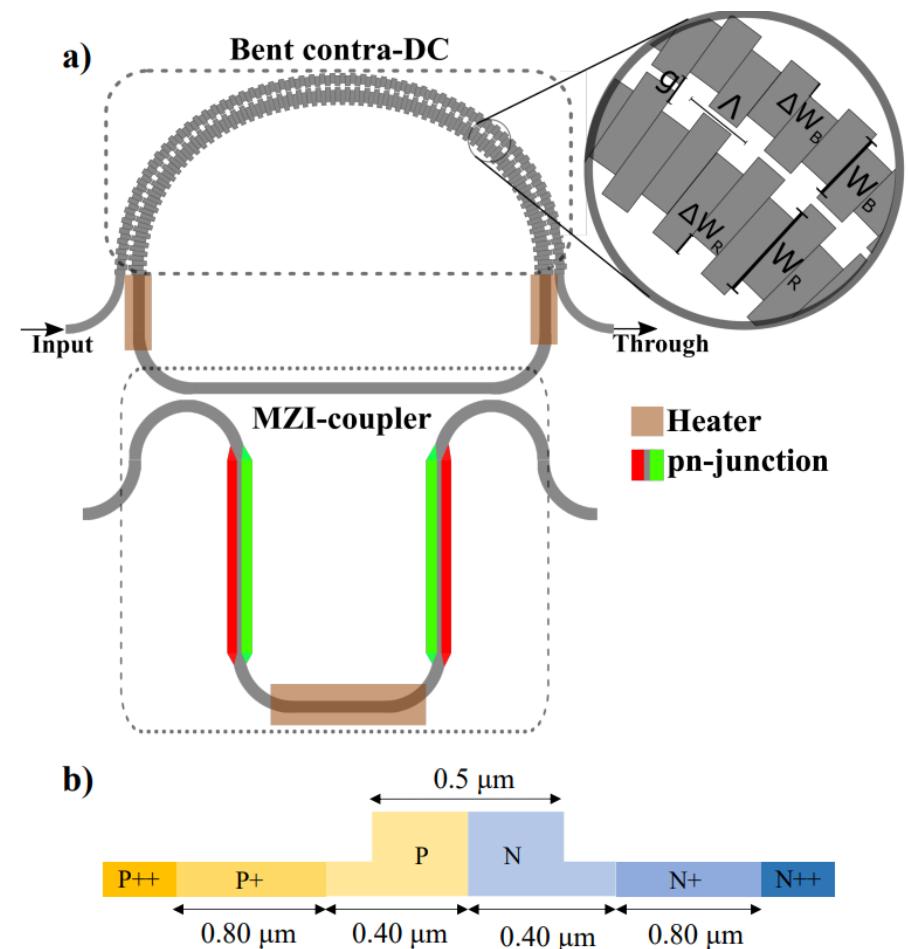
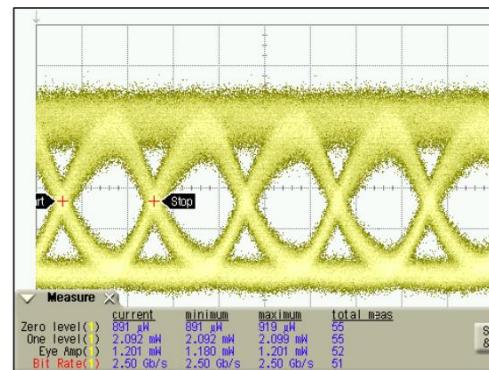
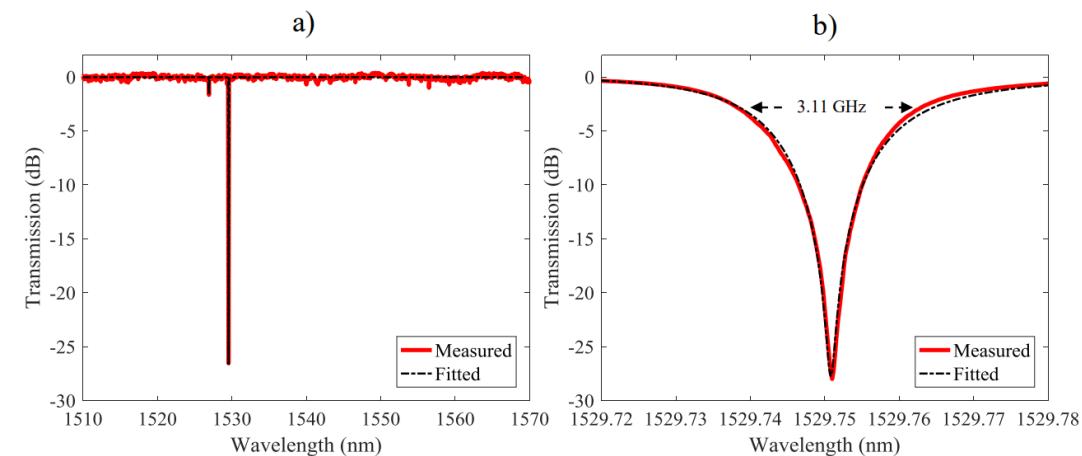
# FSR-FREE RINGS

- Contra-DCs can be integrated into the coupling regions of micro-ring resonators to suppress all the resonances, except those at the Bragg wavelength.



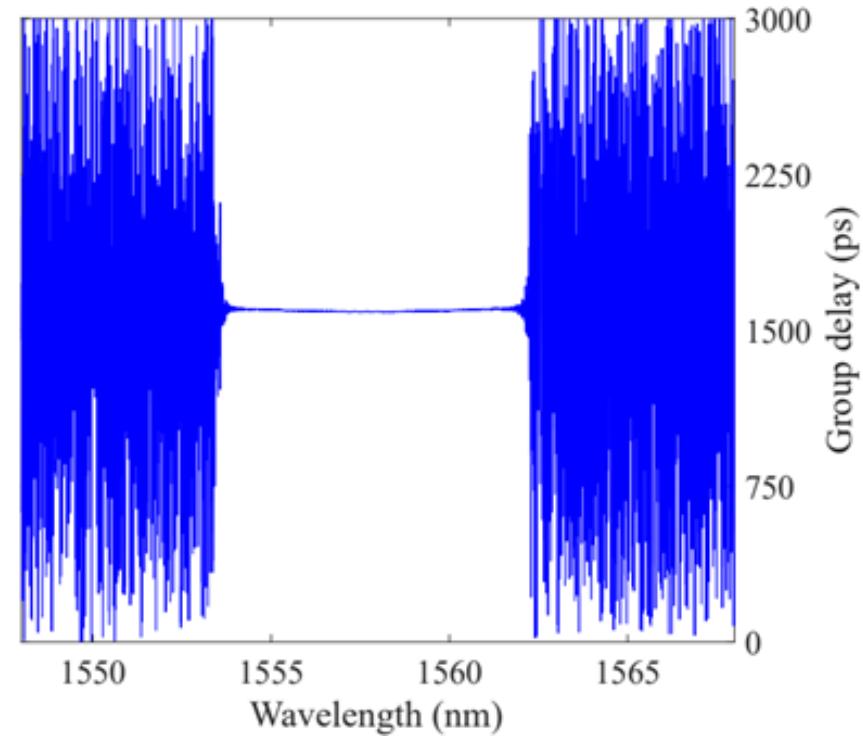
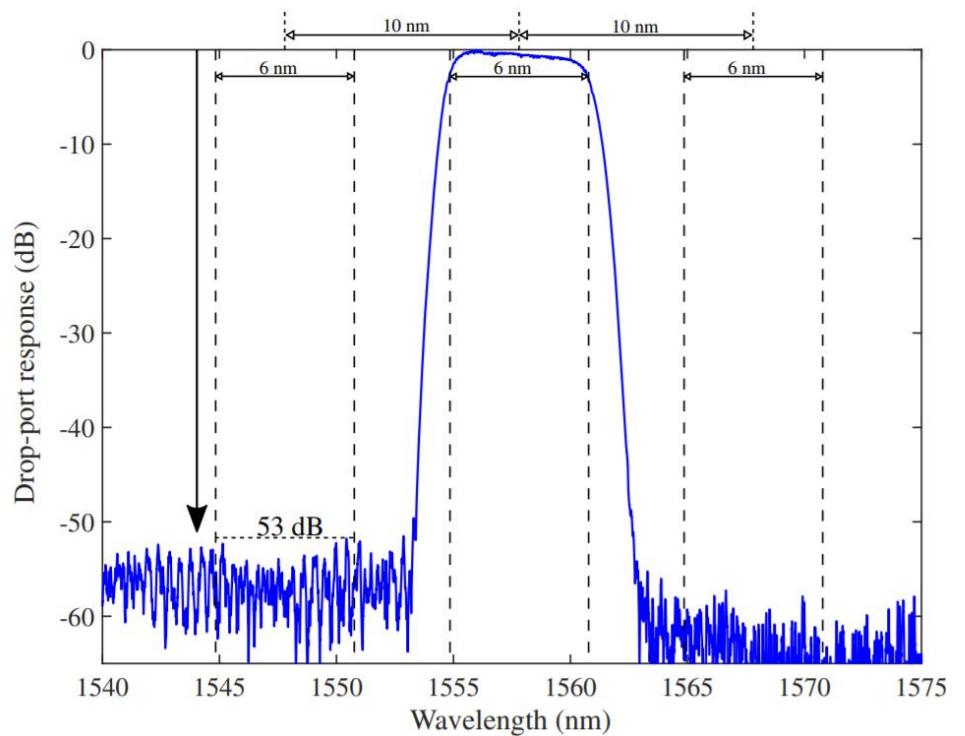
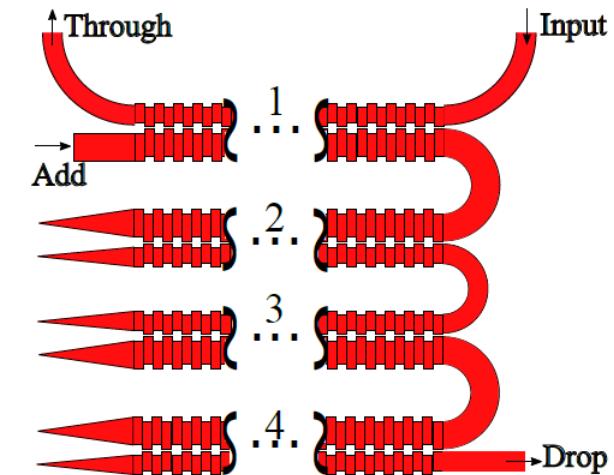
# FSR-FREE RINGS

- Can be turned into an FSR-free ring modulator!



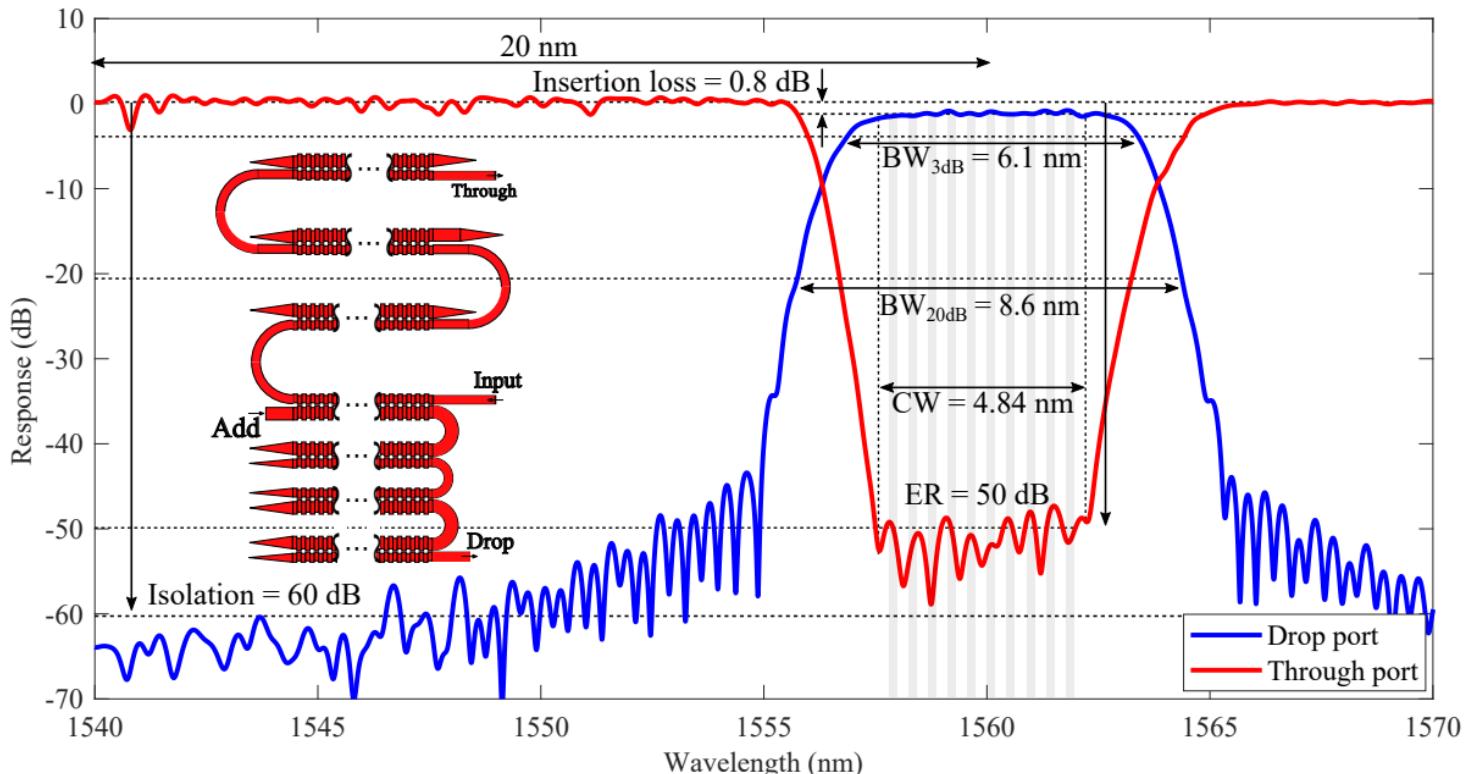
# CASCADED CONTRA-DCS

- Cascading the drop ports of contra-DCs allows designers to suppress the side-lobes while maintaining low insertion losses due to high reflectivity.



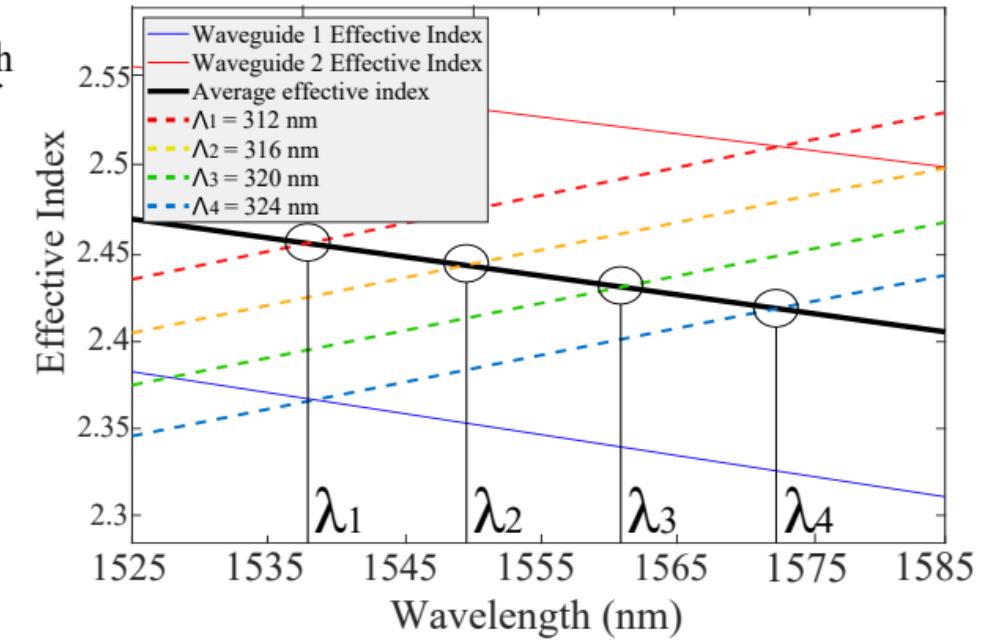
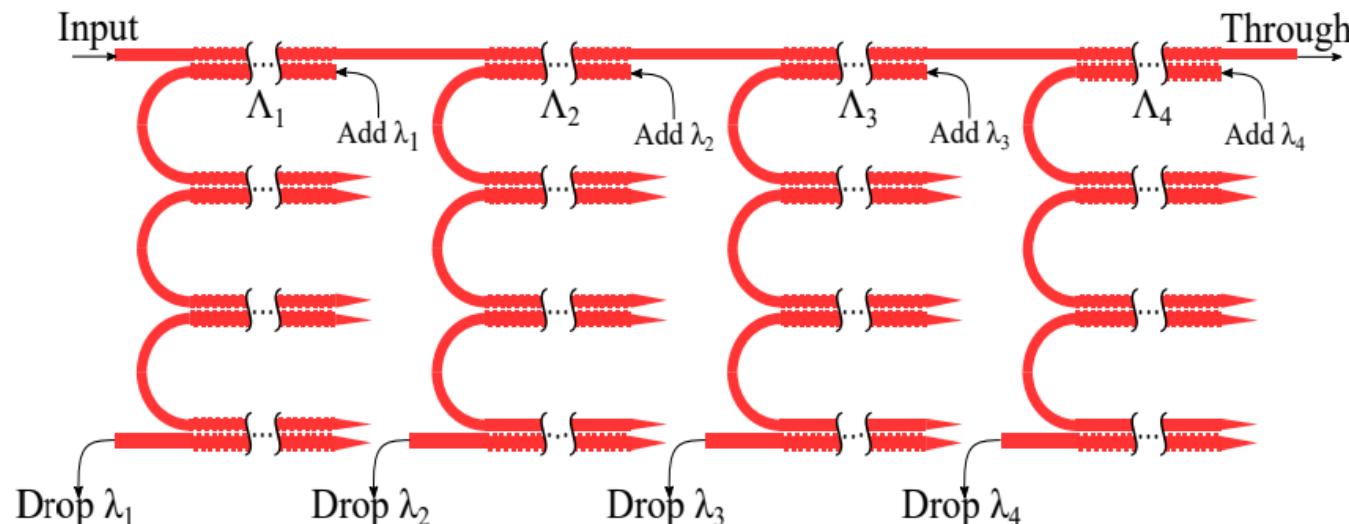
# CASCADED CONTRA-DCS

- Similarly, we can apply the same concept to the **Through-port** and achieve ultra-high extinction ratio filters



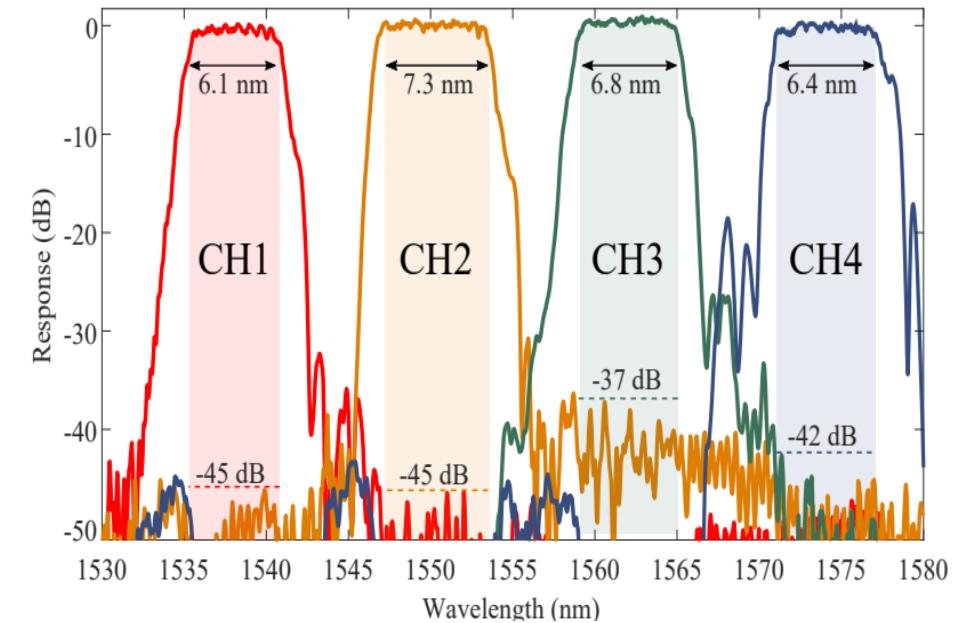
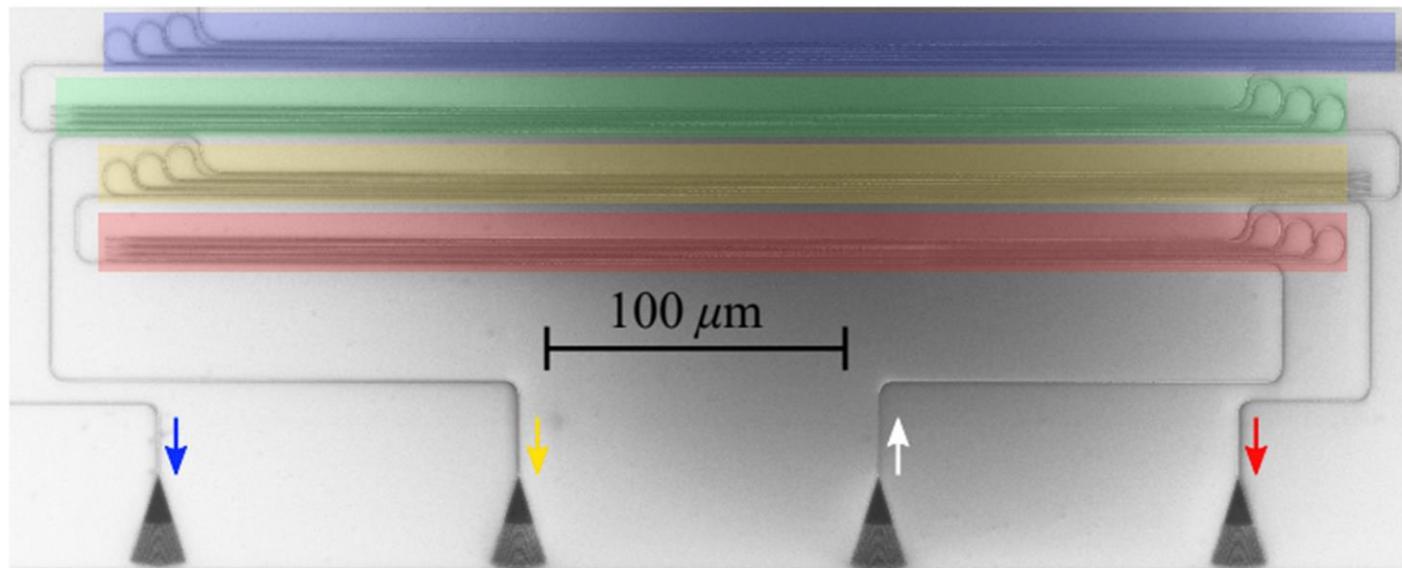
# CASCADED CONTRA-DCS

- Create functional C-WDM filters on silicon with record breaking figures-of-merit!



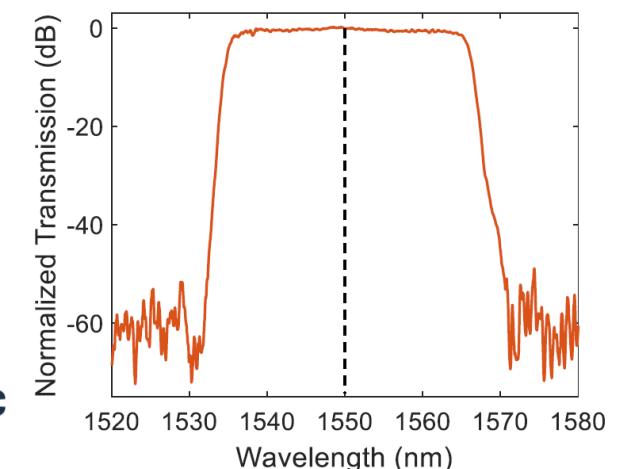
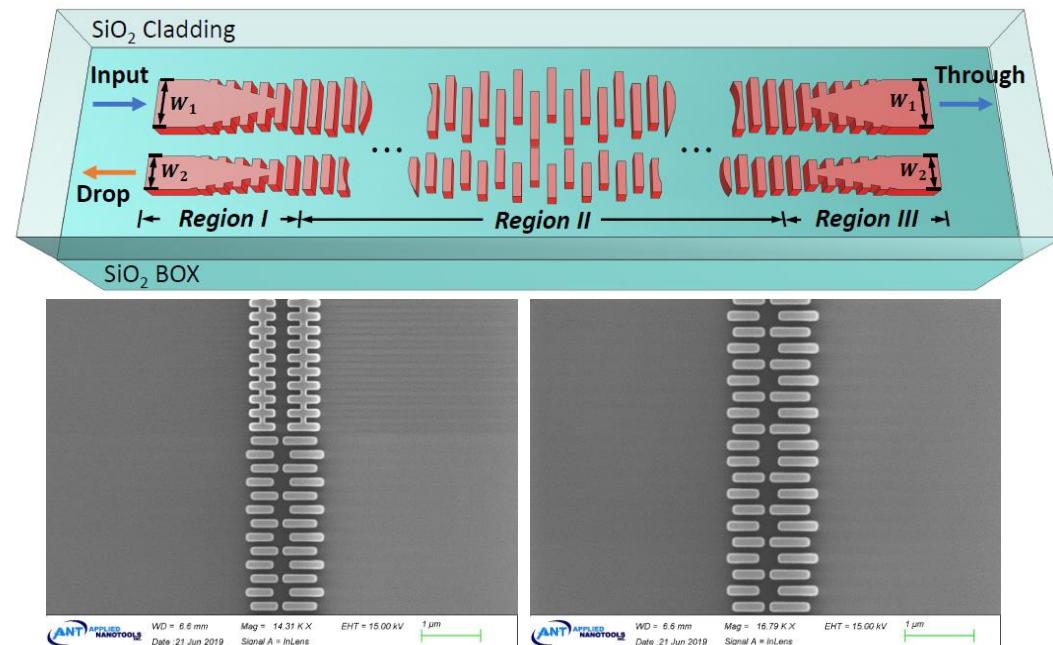
# CASCADED CONTRA-DCS

- Create functional C-WDM filters on silicon with record breaking figures-of-merit!



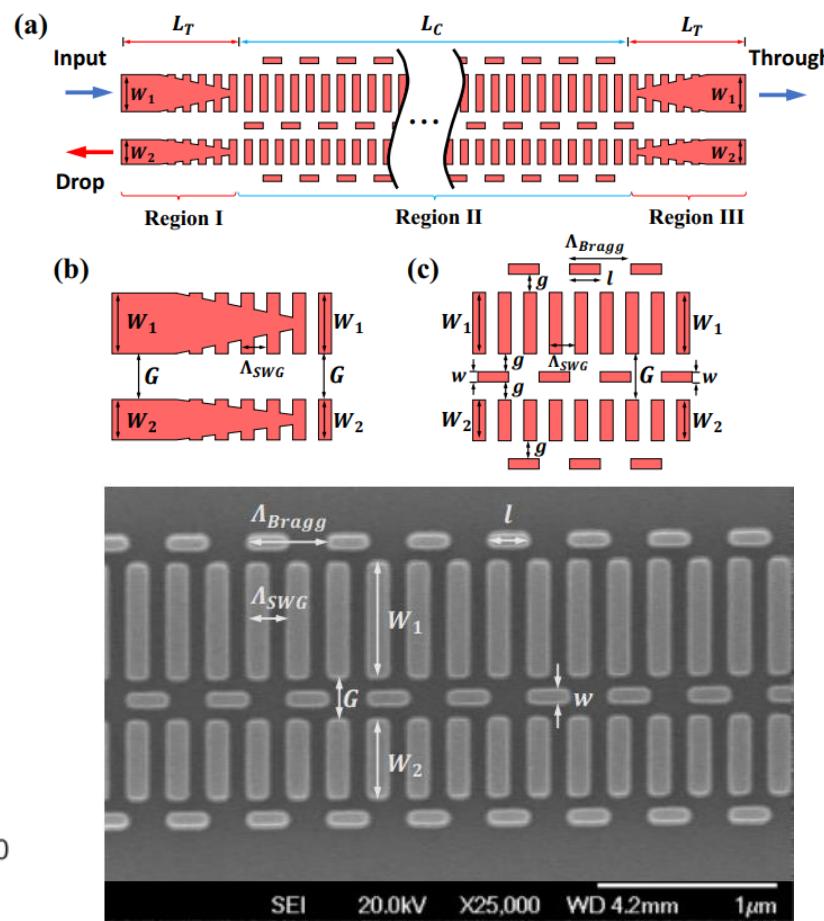
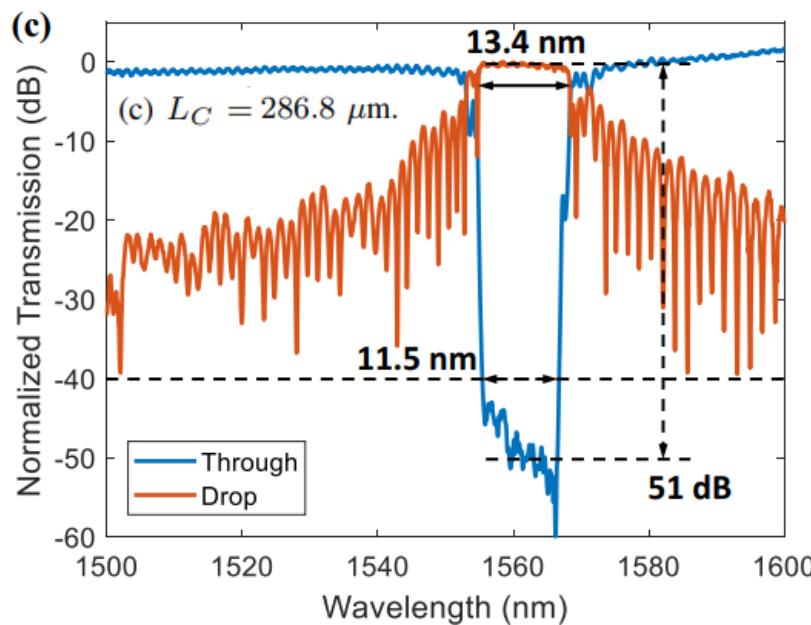
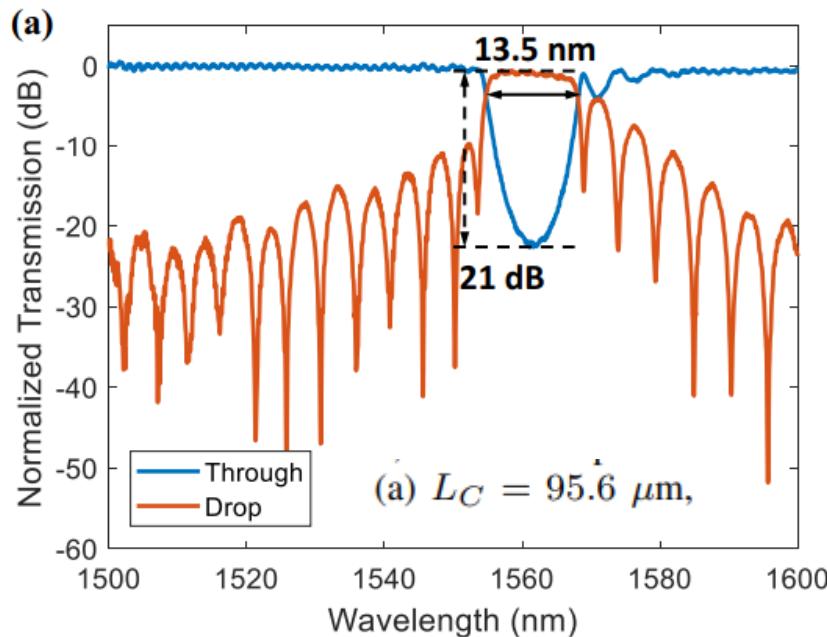
# SUB-WAVELENGTH CONTRA-DCS

- Use sub-wavelength waveguides in a contra-DC configuration
- Low mode-confinement significantly increases the coupling coefficient
  - Significantly shorter devices
  - Wider bandwidths
- **Insertion loss:** <0.85 dB
- **Bandwidth:** up-to 33 nm
- **Isolation:** >55 dB (stacked – 3 stage)



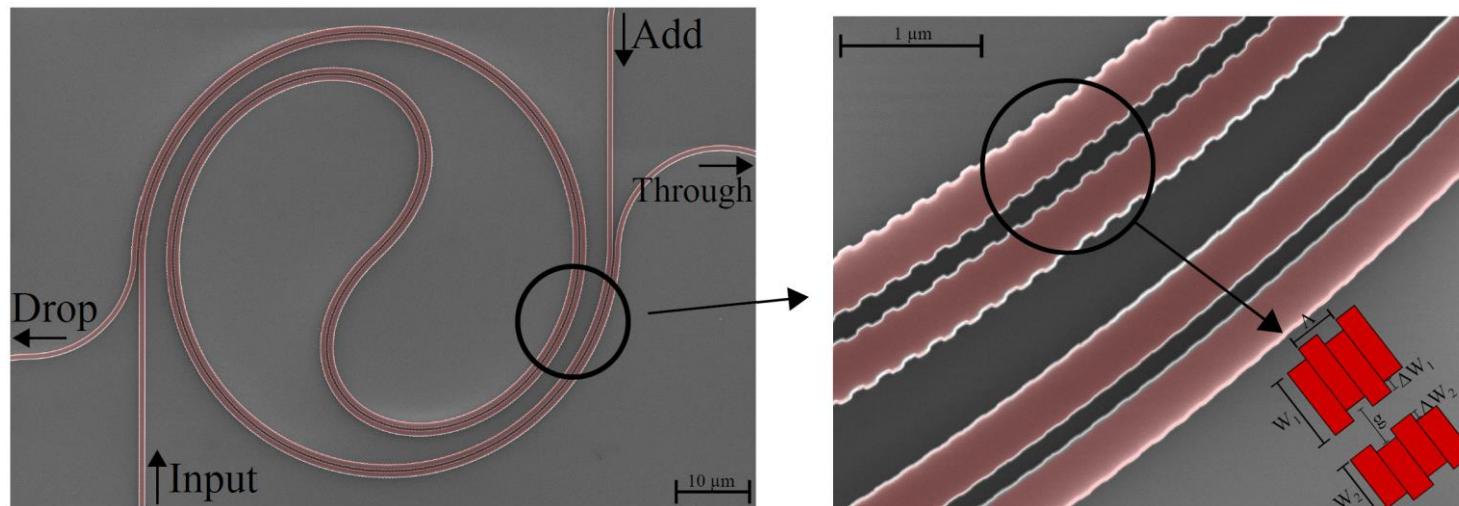
# SUB-WAVELENGTH CONTRA-DCS

- Using unperturbed sub-wavelength waveguides
  - Using cladding modulations:
    - Allows more flexibility to control the coupling strength



# SPIRAL CONTRA-DCS

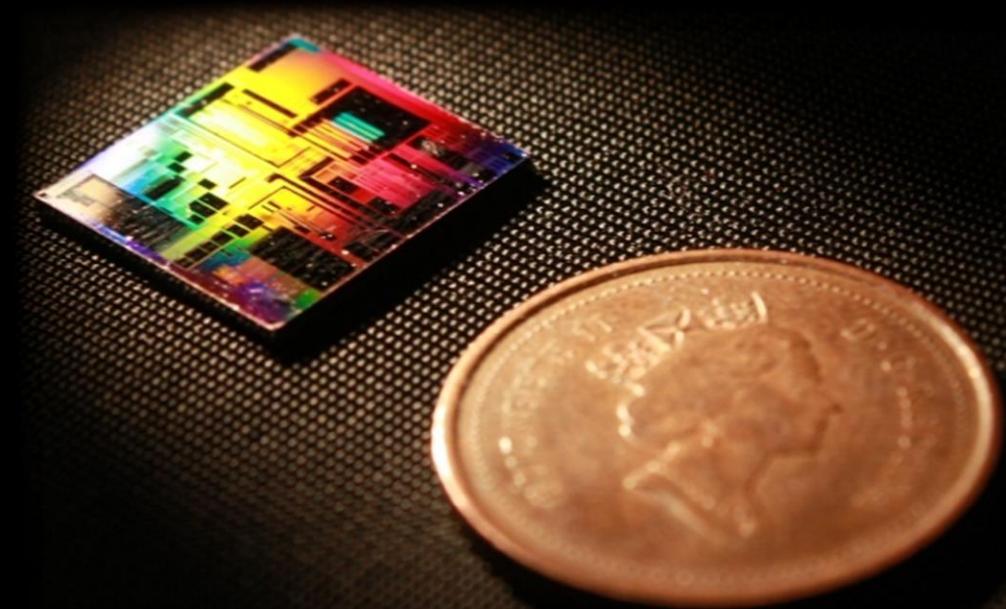
- With more complex perturbation profiles (apodization, chirped, etc.) , greater number of periods is needed.
- High index contrast of silicon vs glass allows us to bend light tightly. We can use Spirals to optimize the
- Consideration the effective index vs bend radius!
- ~2000 Perturbation periods compacted in an area of  $45 \times 45 \mu\text{m}^2$ :



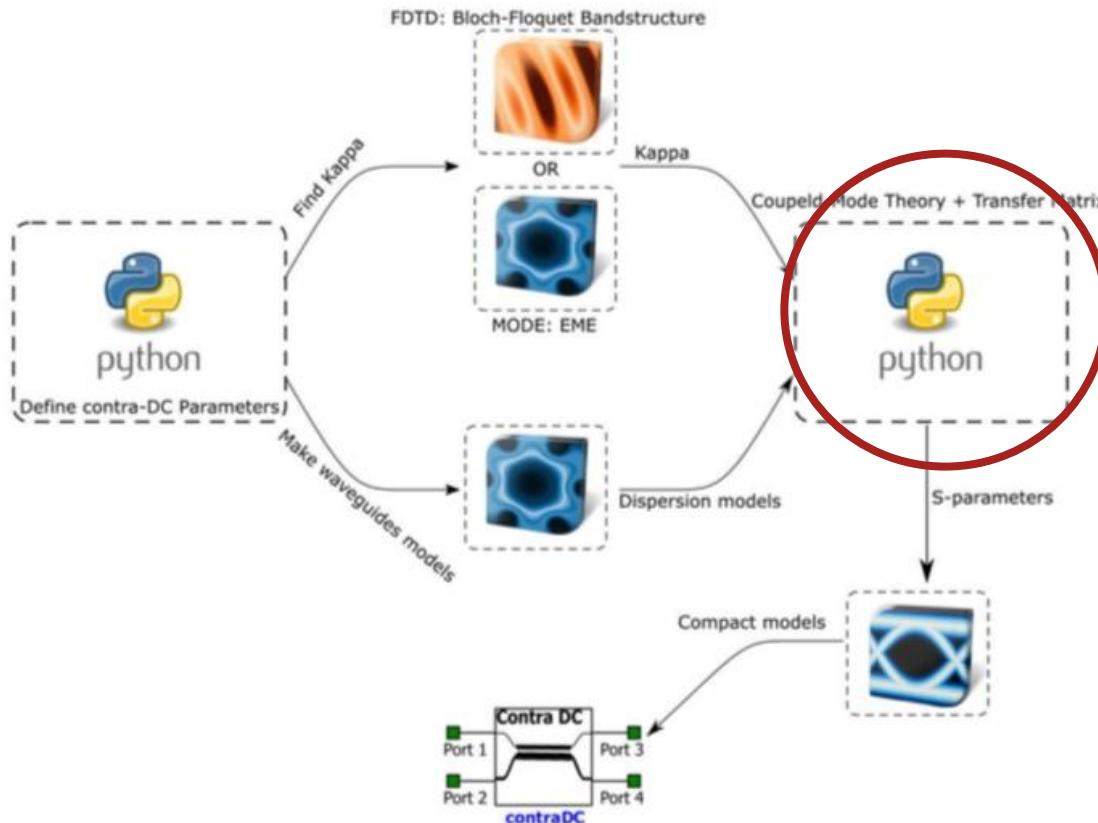
# CONTRA-DIRECTIONAL COUPLERS: SIMULATION

Jonathan Cauchon

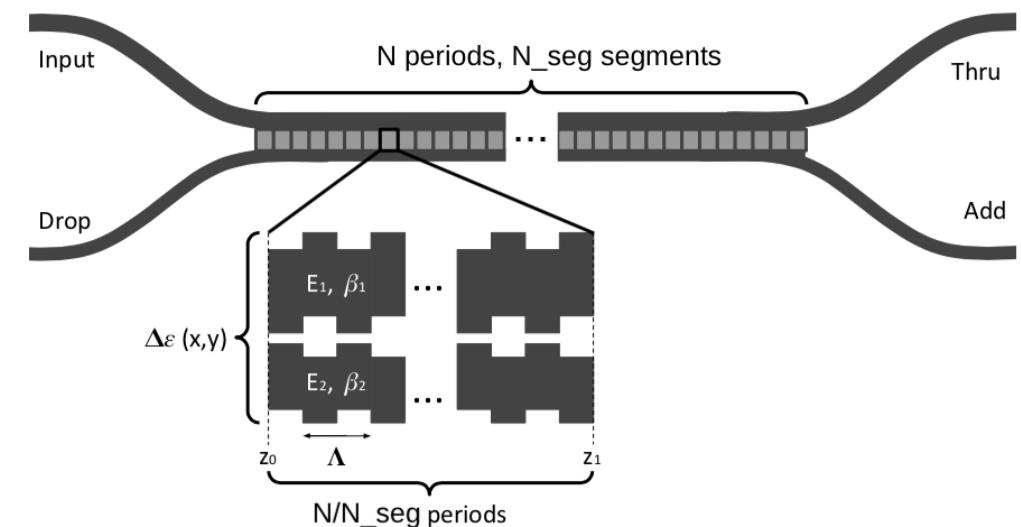
2020-11-26



# TRANSFER-MATRIX MODEL IMPLEMENTATION



- TMM model implemented in Python
- Full parametrization
- Many pre-set configurations to get started quickly
- Main concept: sub-divide a contra-DC into uniform grating segments:



# TO GET STARTED

- Start designing contra-DCs in 5 minutes
- Requirements: Python 3.6+
- Can be run in a Python IDE, Python-building text editor, or Jupyter notebook

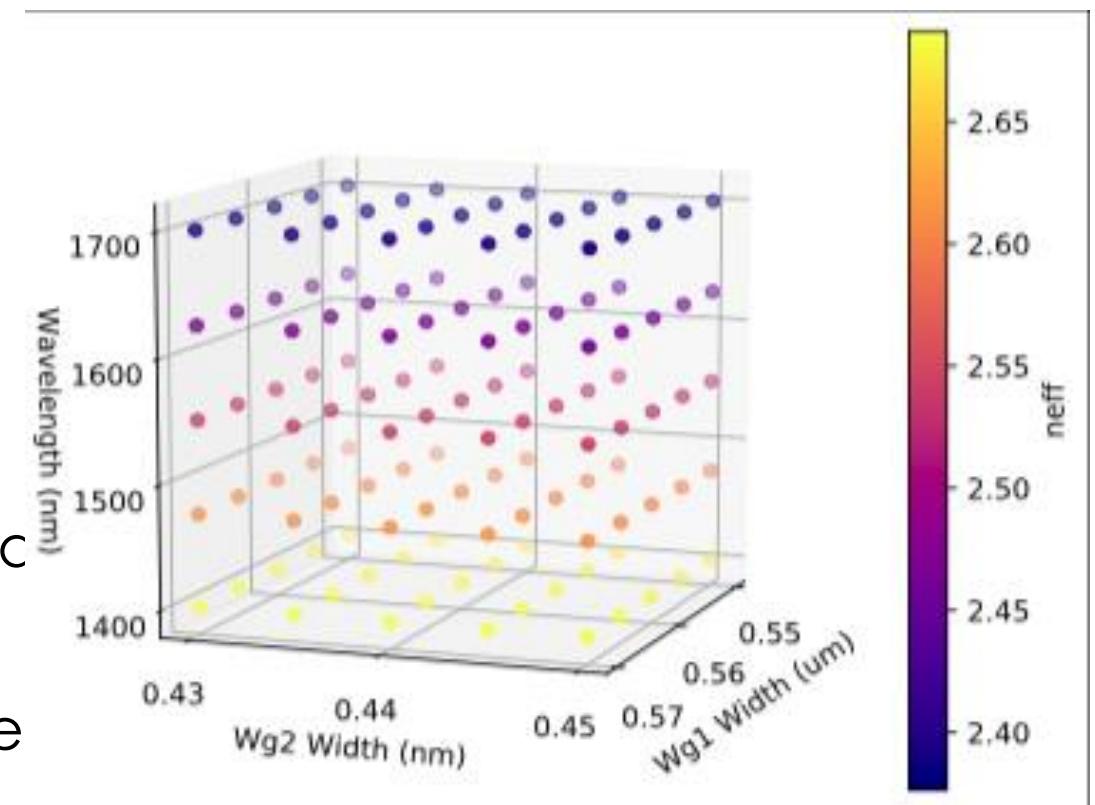
```
git clone https://github.com/JonathanCauchon/Contra-DC
```

- Read the documentation to learn about the member functions and parameters in depth:

<https://jonathancauchon.github.io/Contra-DC/>

# WHAT'S IN THE BOX

- The out-of-the-box program is valid for a subset of devices:
  - Silicon on silica
  - E-Beam process
  - 100-nm gap
  - $550 \text{ nm} < w_1 < 570 \text{ nm}$
  - $430 \text{ nm} < w_2 < 450 \text{ nm}$
- Many MODE simulations were performed for this subset, which makes interpolation possible. You can build your own database



# EXAMPLE 1: CONTRA-DC "HELLO WORLD"

```
""" Example 1: regular SOI Contra-DC """
```

```
# instantiate, simulate and show result
```

```
device = ContraDCC().simulate().displayResults()
```

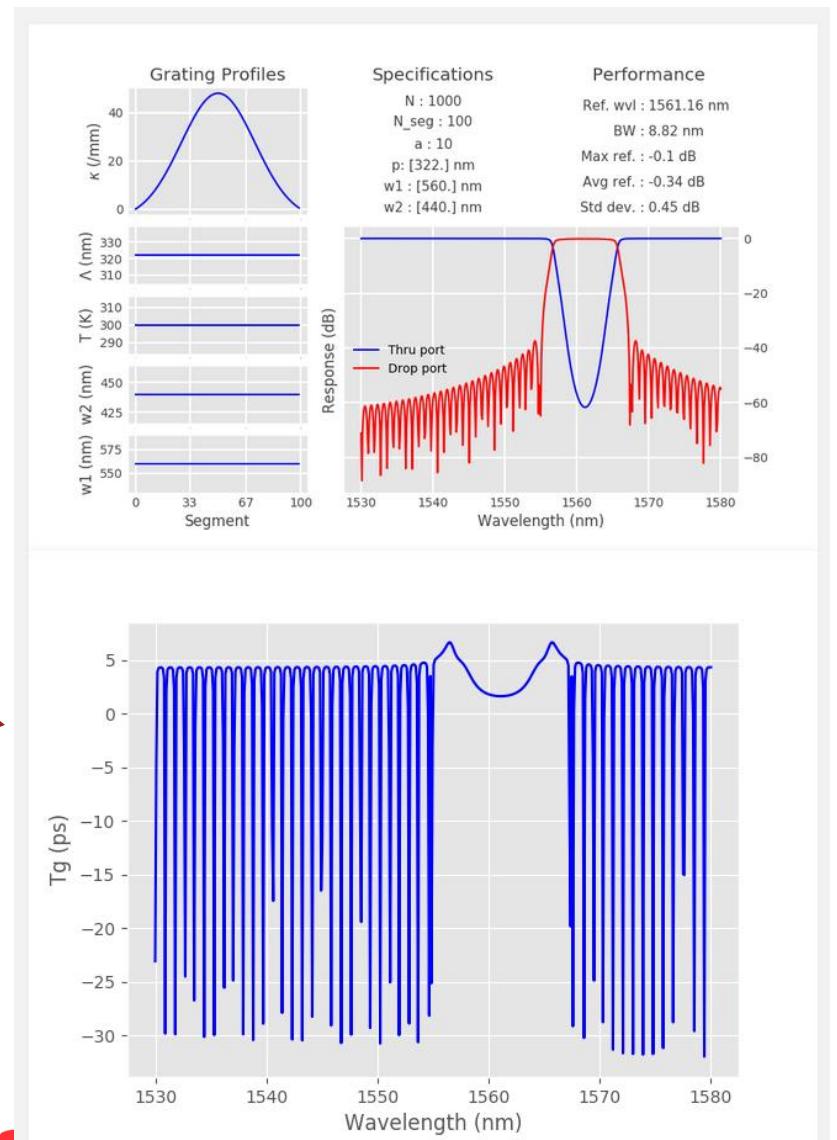
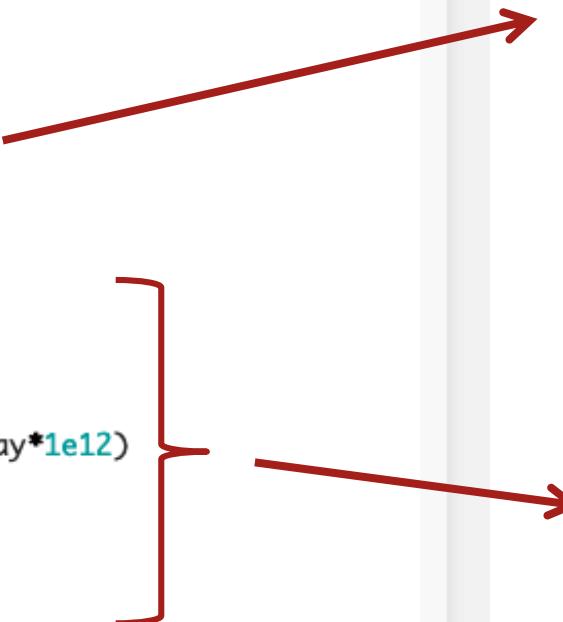
```
# calculate the group delay
```

```
device.getGroupDelay()
```

```
# plot group delay
```

```
plt.figure()  
plt.plot(device.wavelength*1e9, device.group_delay*1e12)  
plt.xlabel("Wavelength (nm)")  
plt.ylabel("Tg (ps)")
```

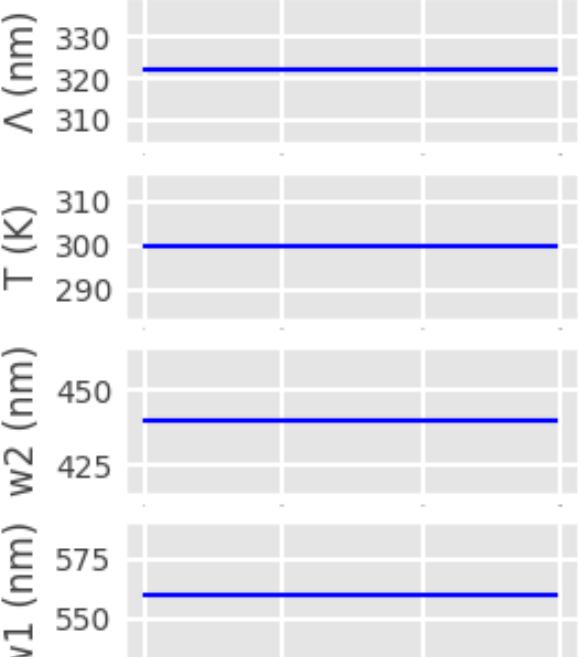
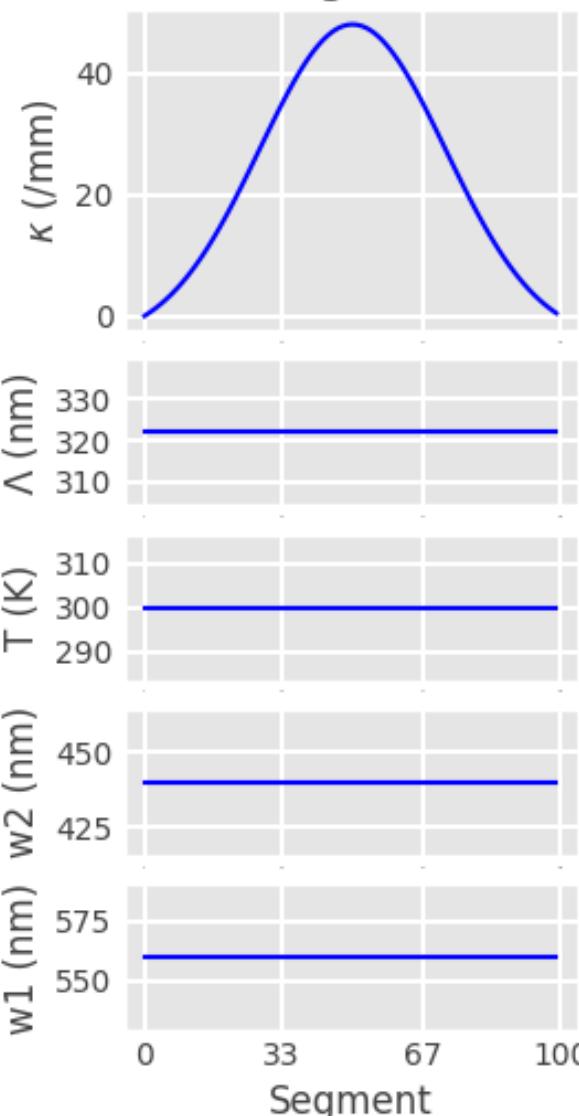
```
plt.show()
```



# PERFORMANCE INTERFACE

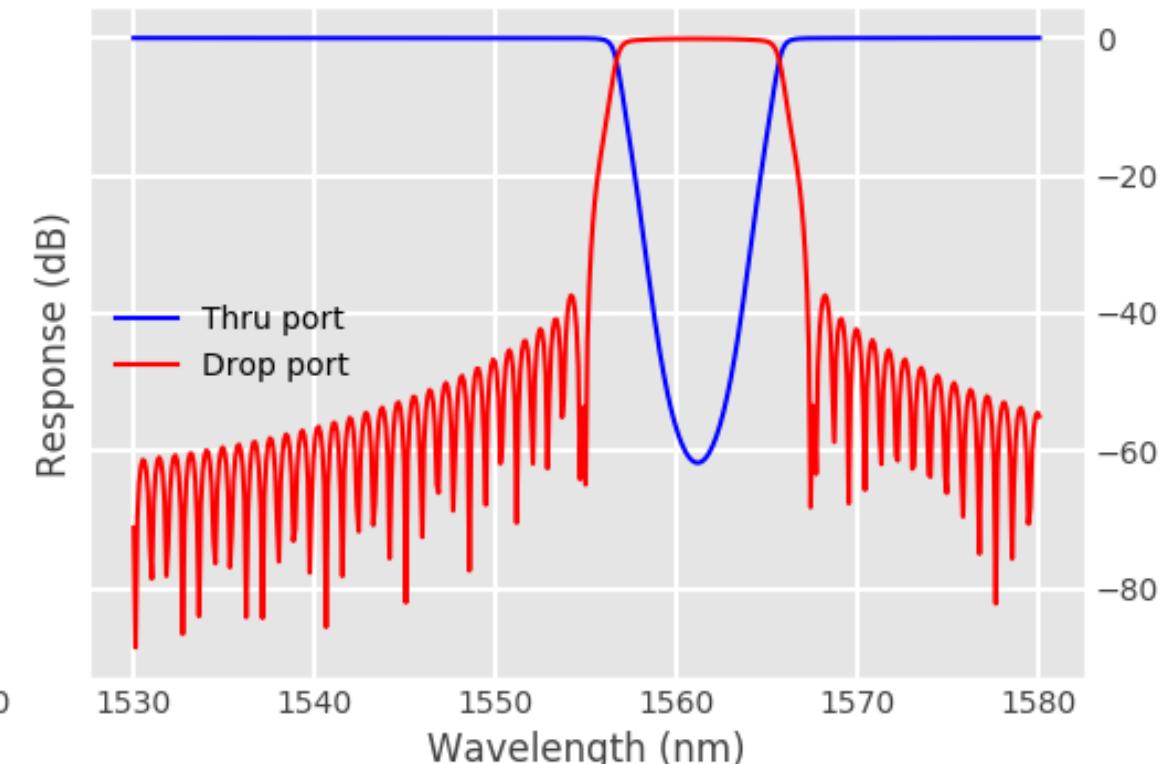
```
ContraDC.displayResults()
```

Grating Profiles



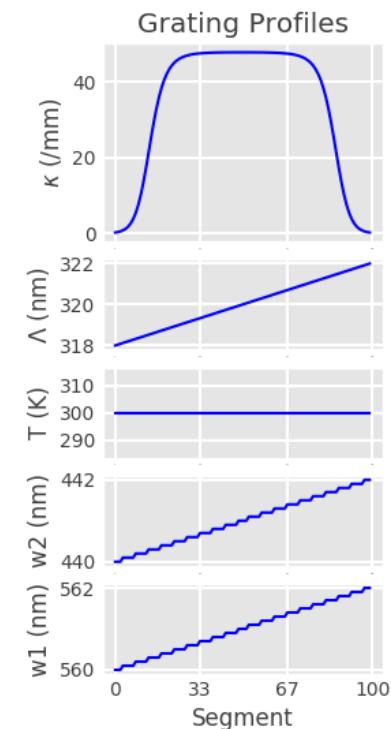
Specifications

N : 1000  
N\_seg : 100  
a : 10  
p: [322.] nm  
w1 : [560.] nm  
w2 : [440.] nm



# EXAMPLE 2: CHIRPED DESIGN

```
""" Example 2: Full chirped example.  
    Create a CDC with chirped w1, w2, period, temperature.  
"""  
  
# Waveguide chirp  
w1 = [.56e-6, .562e-6]  
w2 = [.44e-6, .442e-6]  
w_chirp_step = .1e-9  
  
# Period chirp  
period = [318e-9, 322e-9]  
  
# apod shape  
apod_shape = "tanh"  
  
N = 1200  
  
device = ContraDC(N=N, w1=w1, w2=w2, apod_shape=apod_shape,  
                  w_chirp_step=w_chirp_step, period=period)  
  
device.simulate().displayResults()
```

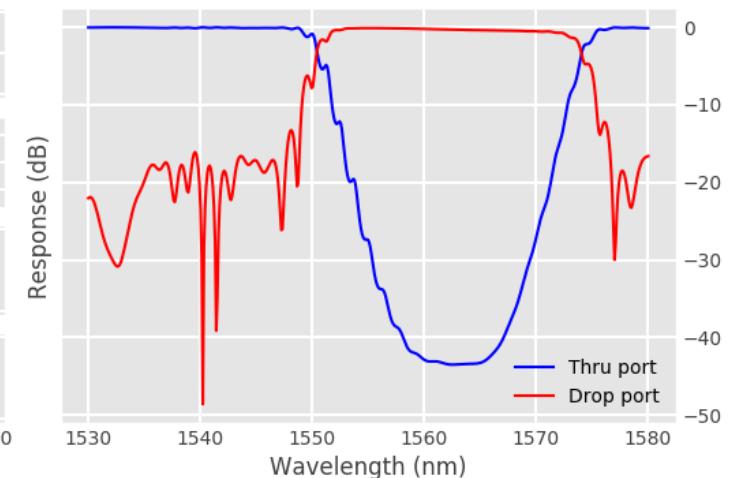


Specifications

N : 1200  
N\_seg : 100  
a : 10  
p: [318. 322.] nm  
w1 : [560. 562.] nm  
w2 : [440. 442.] nm

Performance

Ref. wvl : 1562.21 nm  
BW : 23.55 nm  
Max ref. : -0.11 dB  
Avg ref. : -0.48 dB  
Std dev. : 0.49 dB



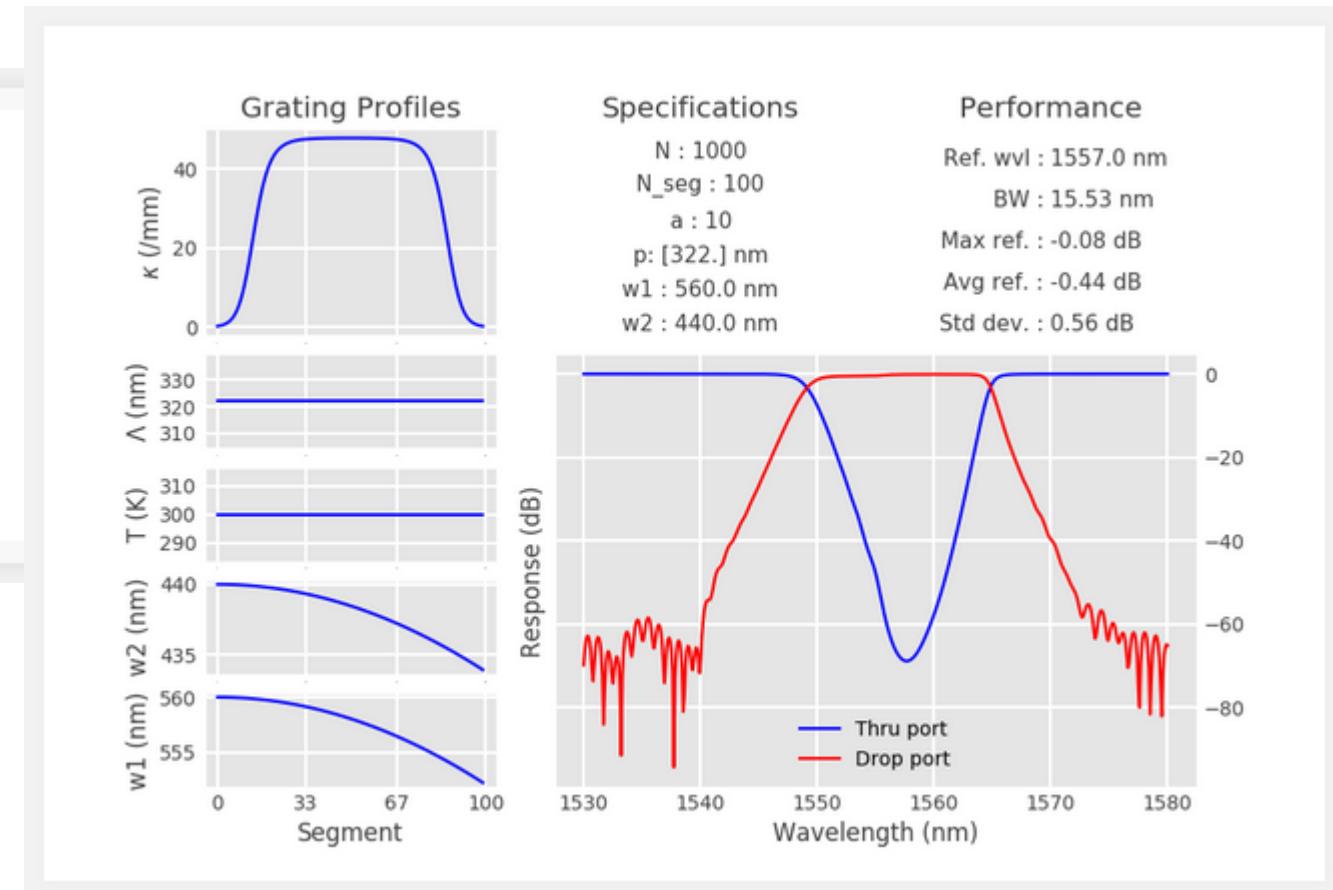
# EXAMPLE 3: CUSTOM CHIRP

```
""" Example 3: defining custom chirp profiles """

device = ContraDC(apod_shape="tanh")

z = np.linspace(0, device.N_seg, device.N_seg)
device.w1_profile = device.w1*np.cos(z/600)
device.w2_profile = device.w2*np.cos(z/600)

device.simulate().displayResults()
```



# EXAMPLE 4: CUSTOM PLATFORM

polyfit.txt

1.5e-06,1.6e-06,1.97004,-201040,1.98997,-257755

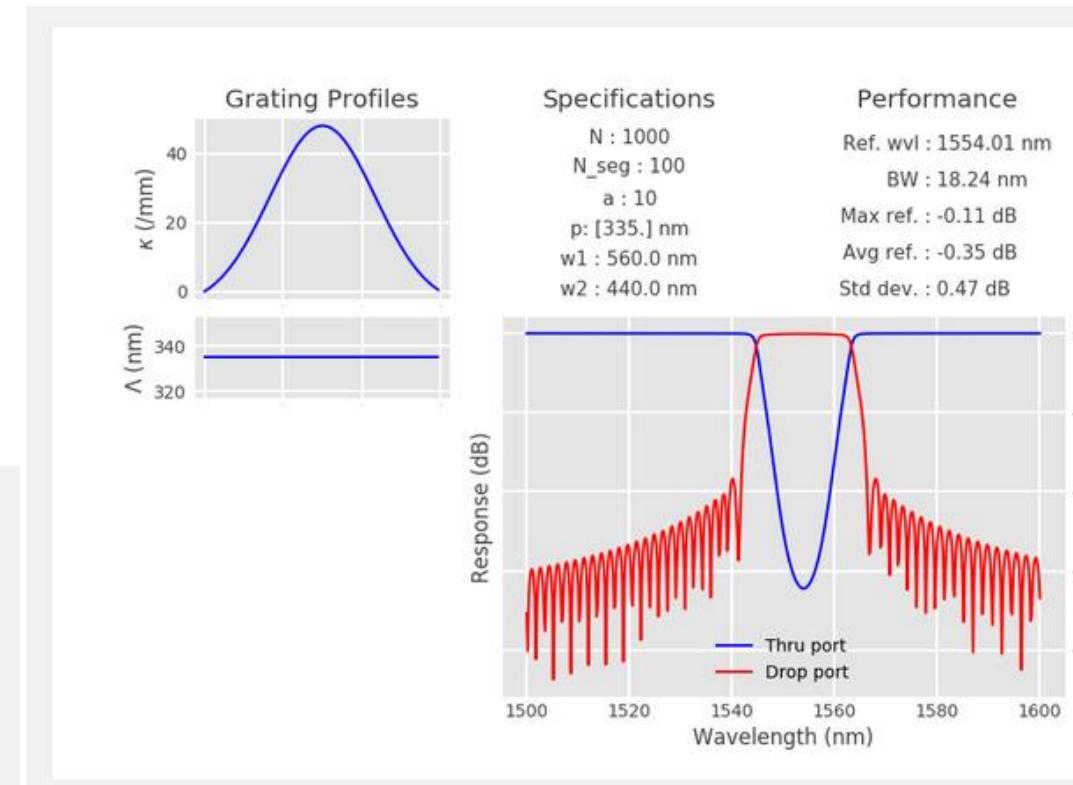
How to get polyfit.txt? **See waveguides->waveguide coupler**

""" Example 4: using custom supermode indices.

You might want to use this if you are designing with silicon nitride, or using other waveguide specs than SOI, 100-nm gap.

"""

```
device = ContraDC(polyfit_file="polyfit.txt", period=335e-9)
device.simulate().displayResults()
```



# EXAMPLE 5: LUMERICAL-ASSISTED

- Lumerical Generate S-parameters
- Lumerical imports S-parameters into INTERCONNECT

# ACKNOWLEDGEMENTS

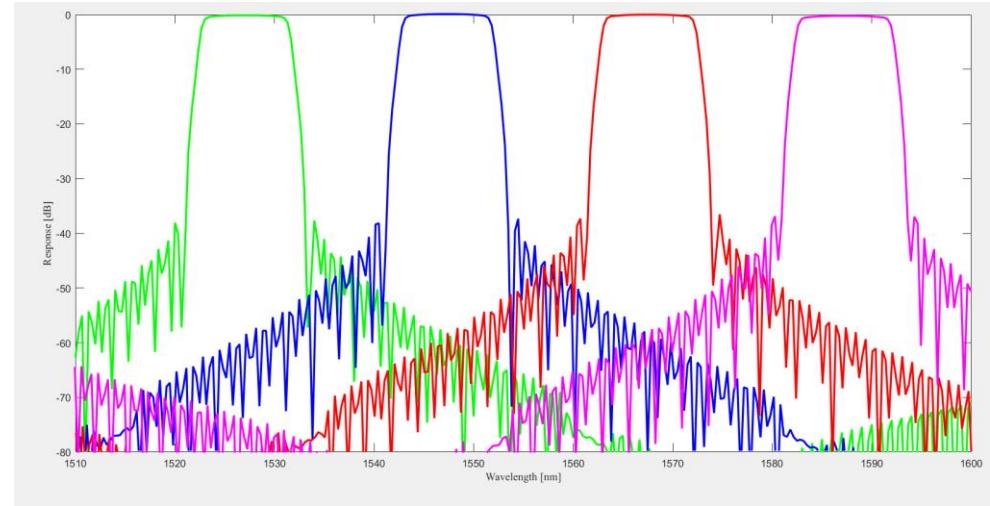
- Keysight Technologies for their financial support on these projects.
- The Natural Sciences and Engineering Research Council (NSERC) of Canada and Canadian Microsystems Corporation (CMC).
- EBeam Fabrication was done at Applied Nanotools and the University of Washington Microfabrication/Nanotechnology User Facility, a member of the NSF National Nanotechnology Infrastructure Network (NNIN). Optical lithography was done at the Institute of Microelectronics (IME)/ Advanced Micro Foundry (AMF) at Singapore through Keysight Technologies.



# DESIGN ACTIVITIES

# ACTIVITY 1

- Design a 4-channel CWDM (de)multiplexer
  - Around the C-Band
  - Full 3-dB bandwidth: 13 nm
  - channel spacing: 20 nm
- Plot your channel responses in a single figure
- Think about how to connect each channel to its neighboring channel.
  - Input waveguide: wide? Narrow? Think about the self-reflection
  - Reduce cross-talk: Apodization? Cascaded filters?
- Refer to Intel Si-Photonics 100G CWDM4 and 400G CWDM8 Transceivers:
  - 100G CWDM4: <https://www.intel.ca/content/www/ca/en/architecture-and-technology/silicon-photonics/optical-transceiver-100g-cwdm4-qsp28-brief.html>



# ACTIVITY 2

- Design a C-band optical add-drop filter
  - C-band bandwidth 1530 nm – 1565 nm
  - Think of the best way to design a filter with such bandwidth.